

SCHEMATIC DIAGRAM OF CONVENTIONAL EXCIMER LASER ANNEALER

FIG. 1 PRIOR ART

FIG.2A
PRIOR ART

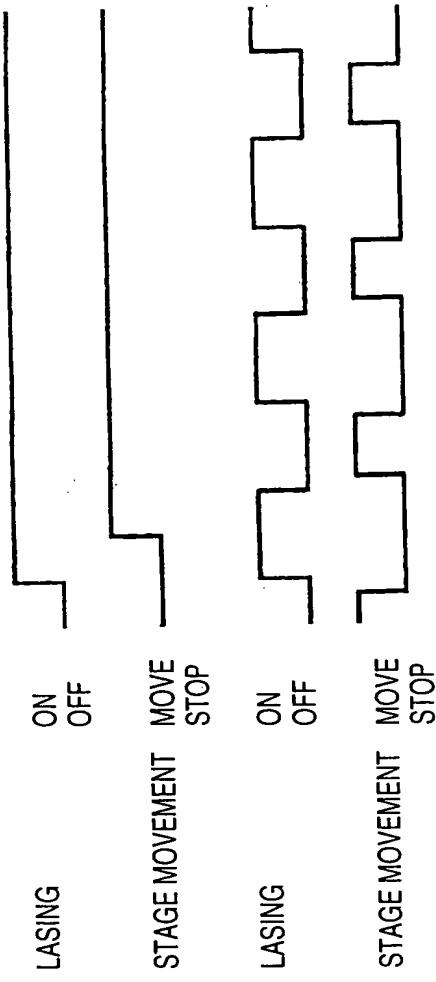


FIG.2B
PRIOR ART

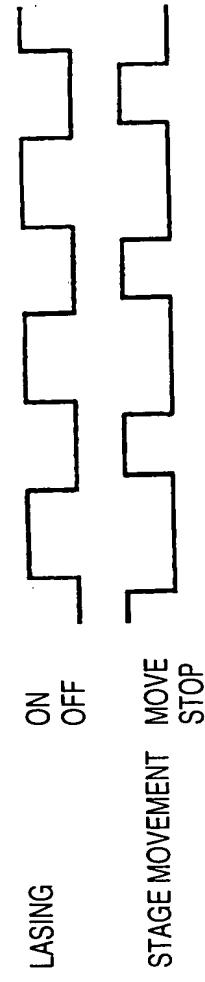


FIG.2C
PRIOR ART

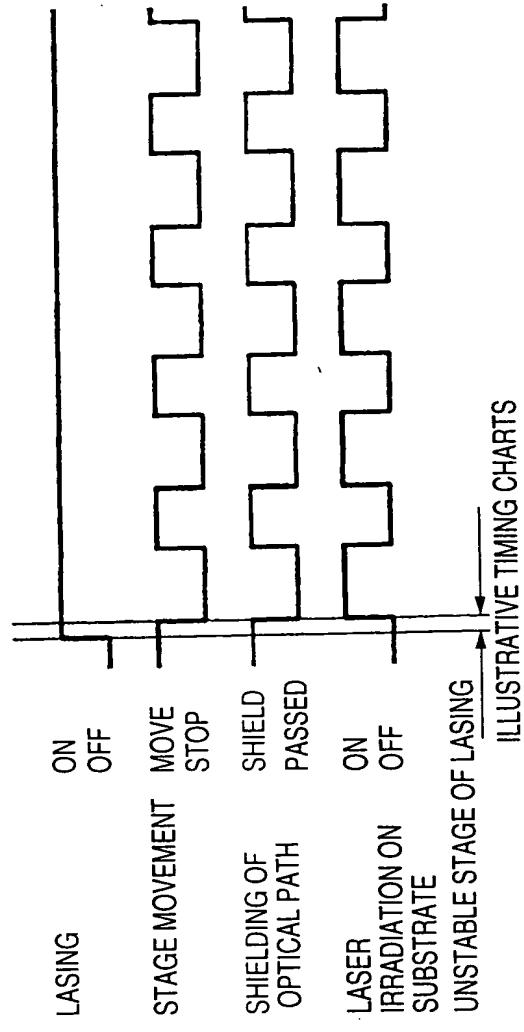


FIG.2D
PRIOR ART

ILLUSTRATIVE TIMING CHARTS

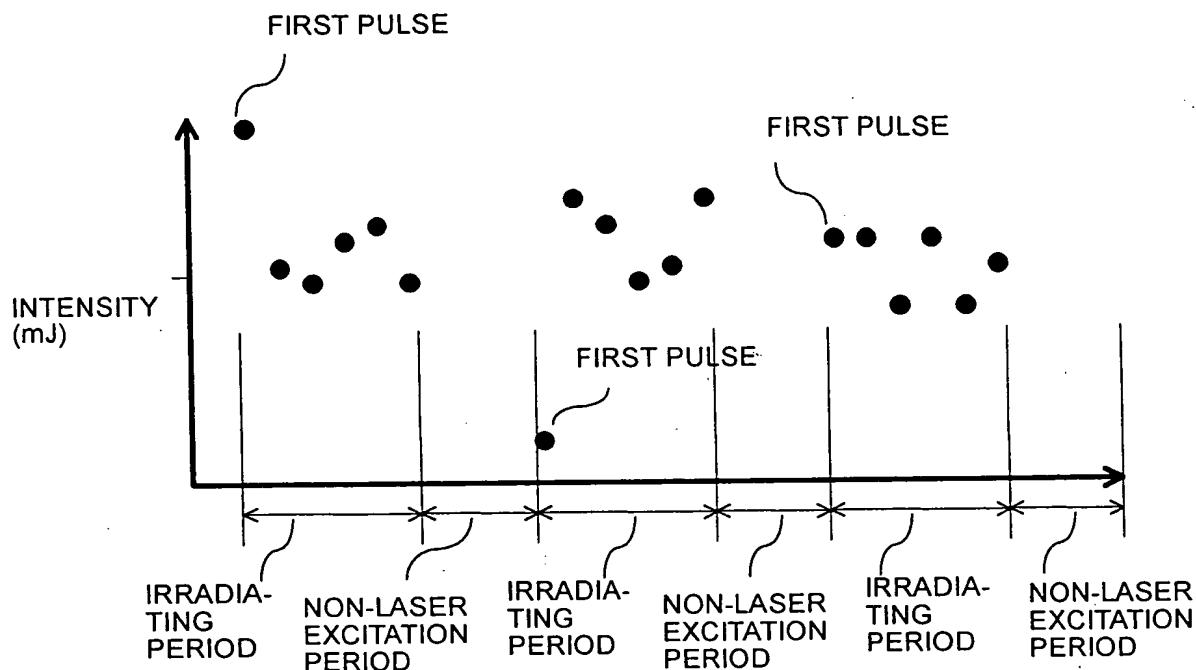


FIG. 3

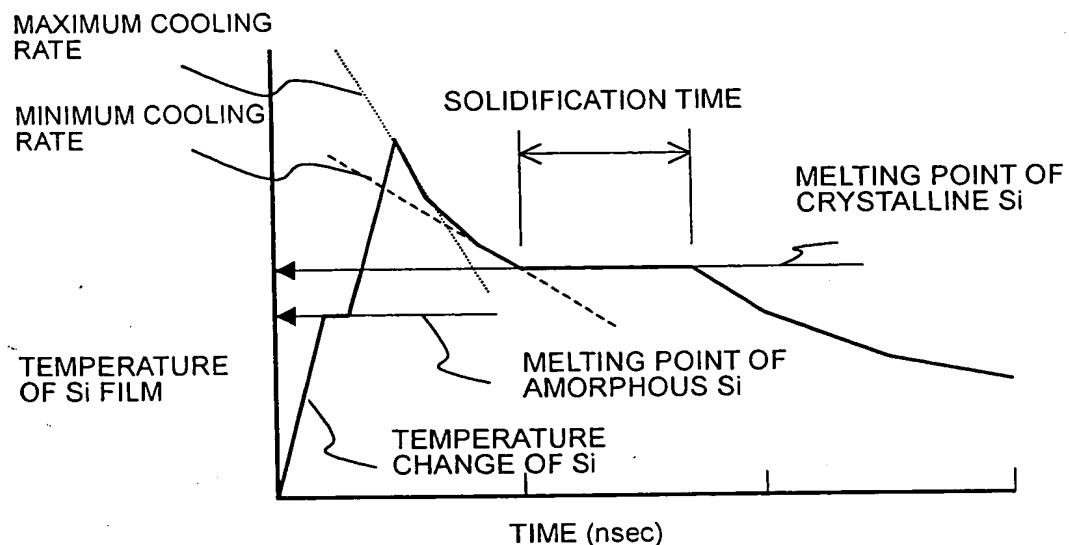
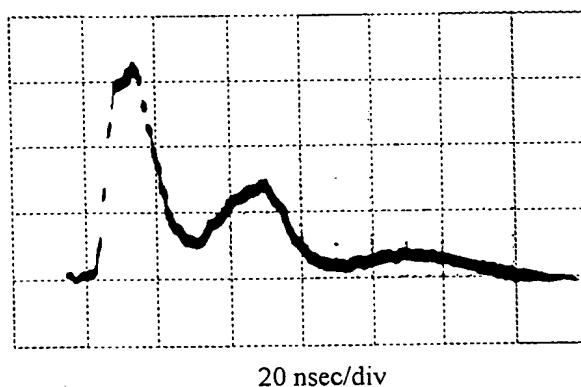
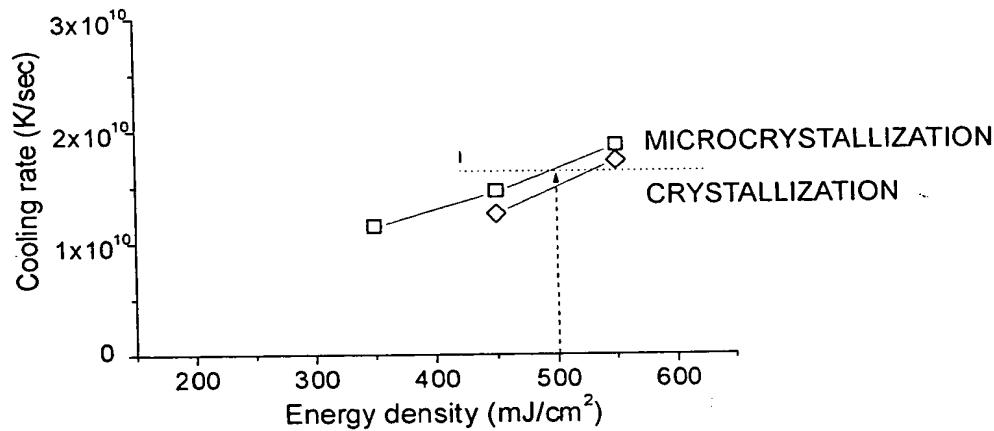


FIG. 4



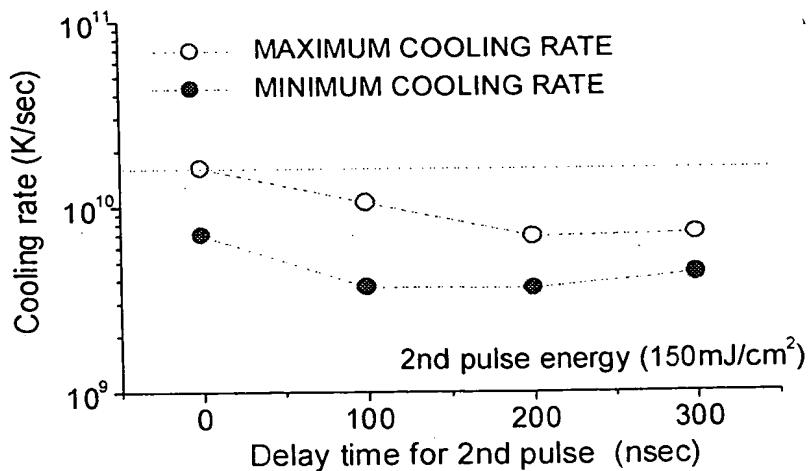
ILLUSTRATIVE LASER PULSE SHAPE

FIG. 5



RELATIONSHIP BETWEEN IRRADIATION INTENSITY AND COOLING RATE,
AND COOLING RATE AT WHICH THE MATERIAL BECOMES AMORPHOUS

FIG. 6



RELATIONSHIP BETWEEN MAXIMUM COOLING RATE AFTER
APPLICATION OF SECOND PULSE AND THE COOLING RATE IN THE
VICINITY OF SOLIDIFICATION POINT

FIG. 9

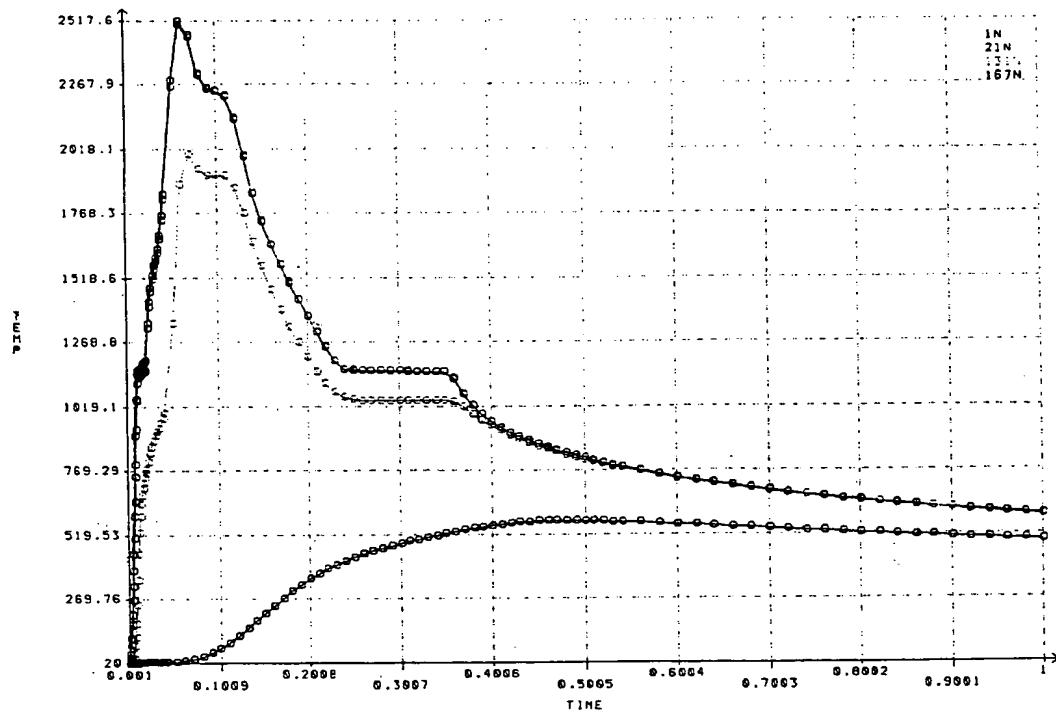
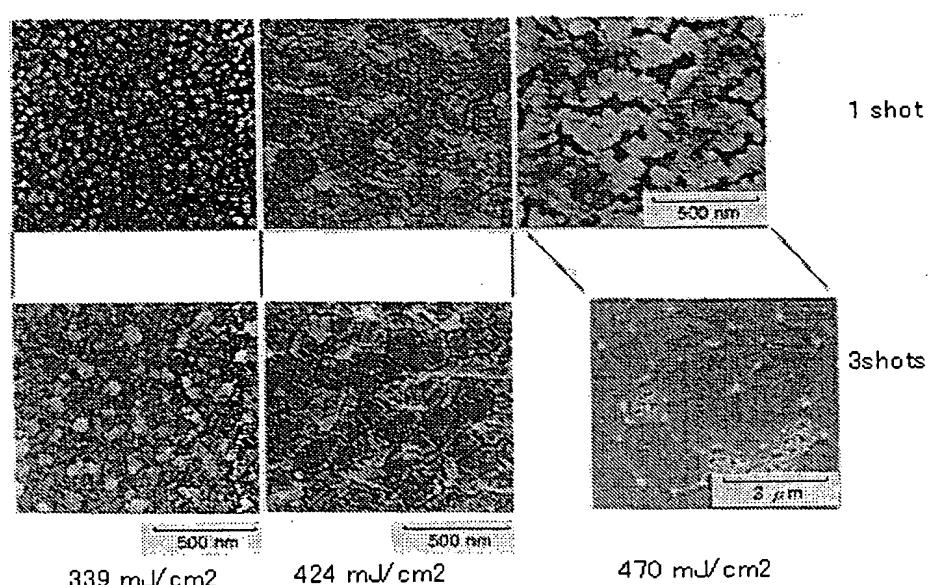


FIG. 7



ELECTRON MICROSCOPIC PHOTOGRAPHS OF LASER-INDUCED CRYSTALLIZED FILMS AFTER ZERO-ETCHING RELATIVE TO IRRADIATION INTENSITY AND NUMBER OF IRRADIATION TIME

FIG. 8

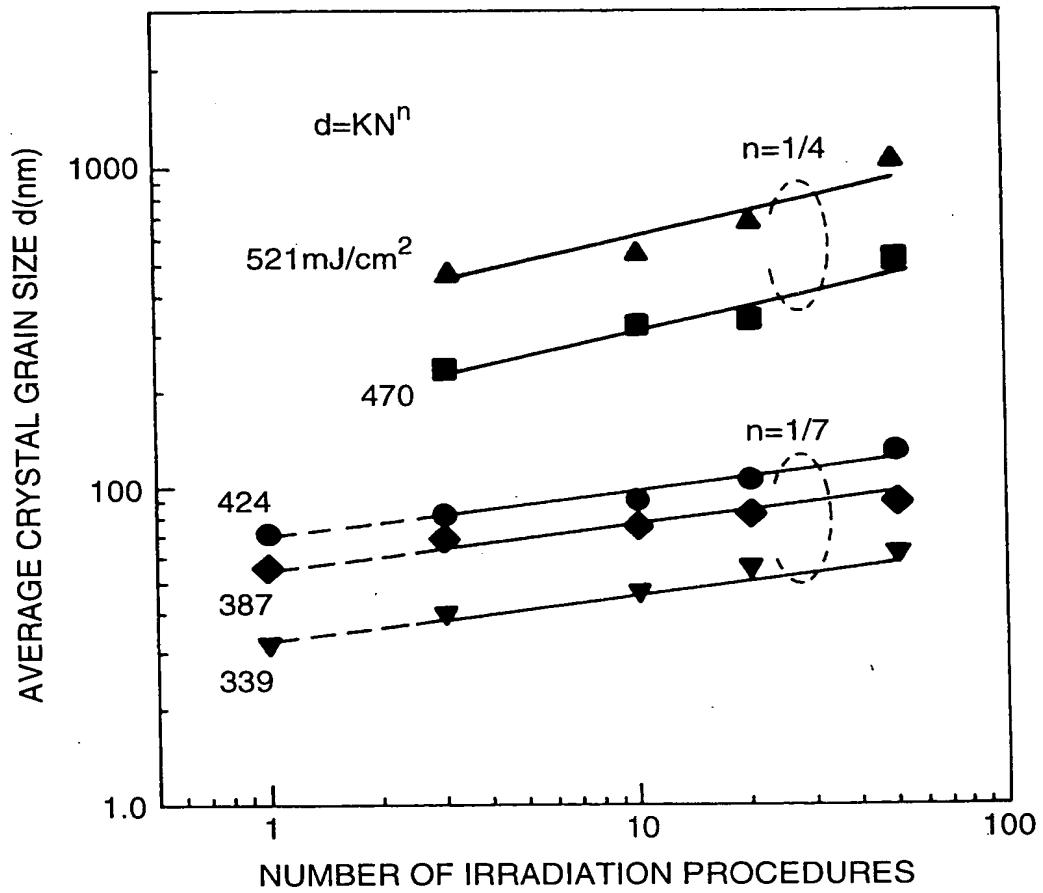
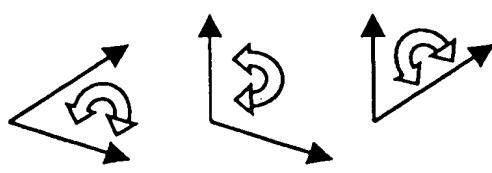
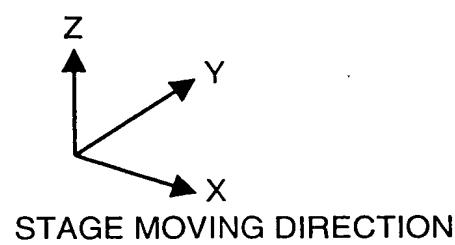
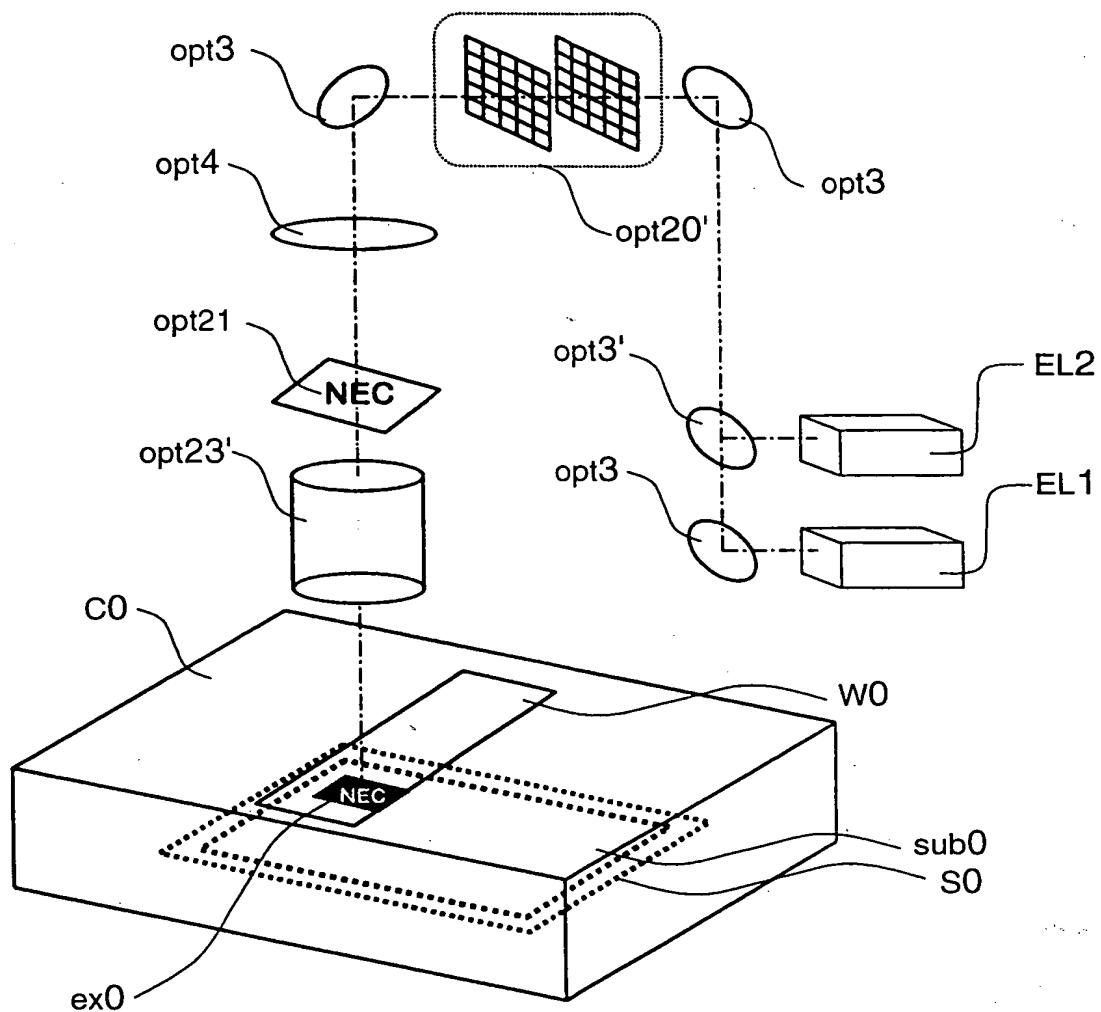
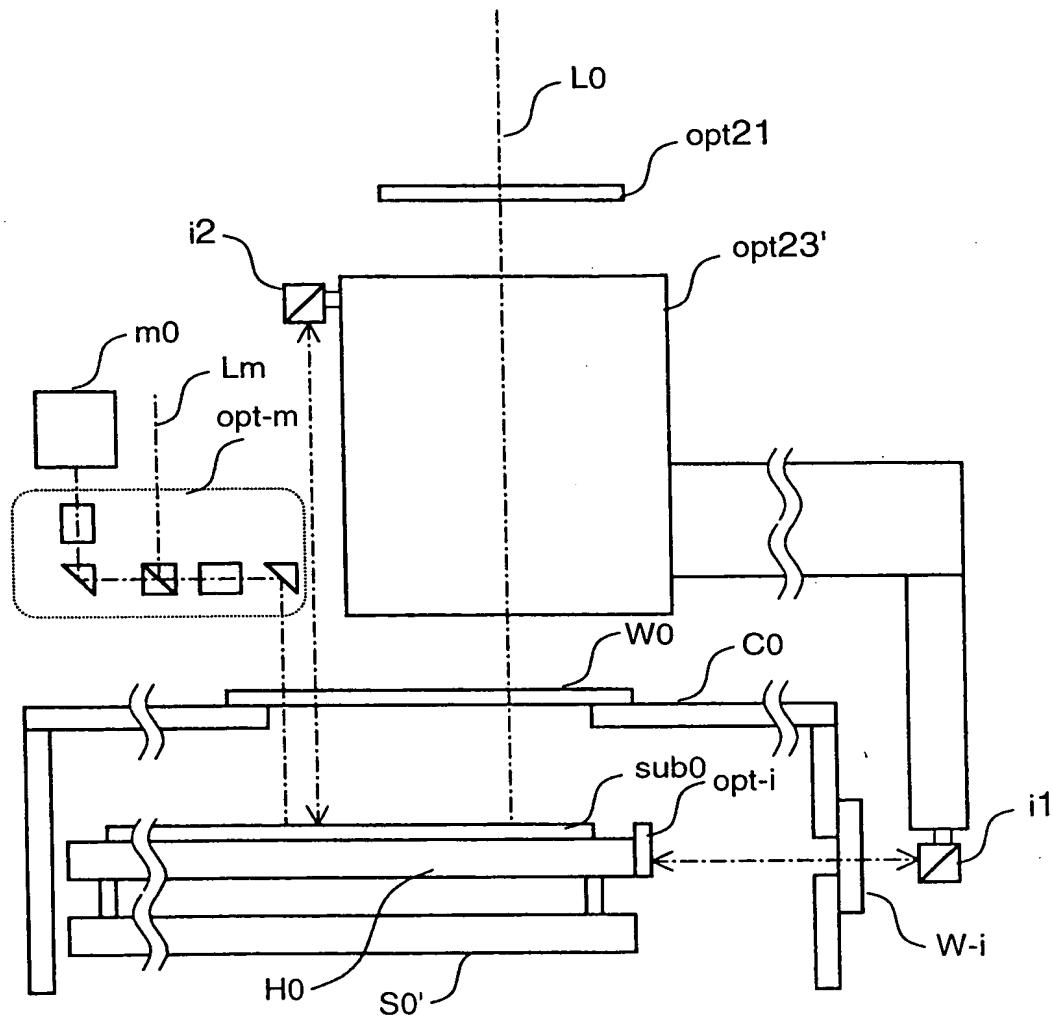


FIG.10



EXCIMER LAYER IRRADIATOR

FIG.11



ALIGNMENT MECHANISM

FIG.12

FIG.13A
MASK
PATTERN

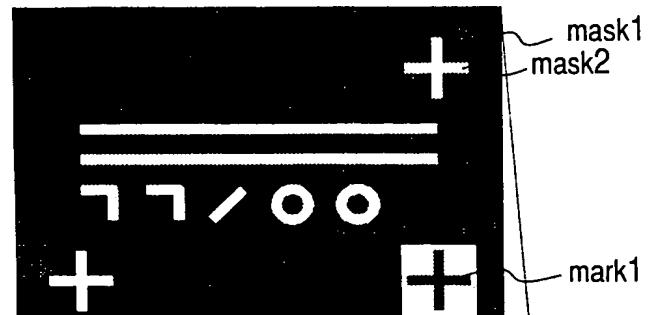


FIG.13B
EXPOSURE
PATTERN

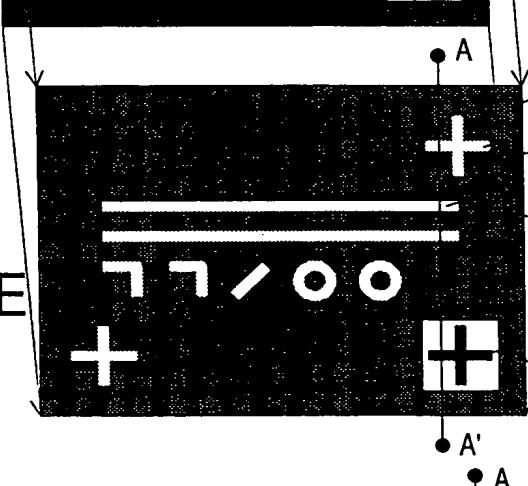
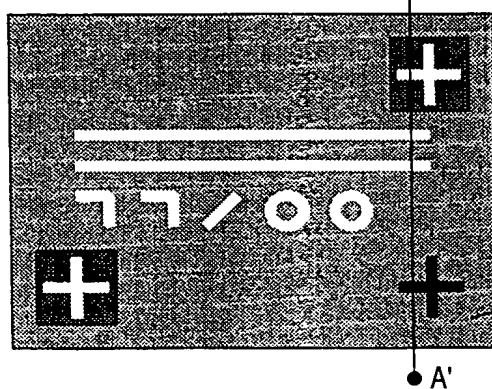


FIG.13D
ETCHING
PATTERN



A-A' CROSS SECTION

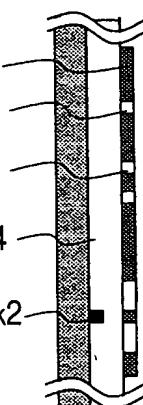


FIG.13C

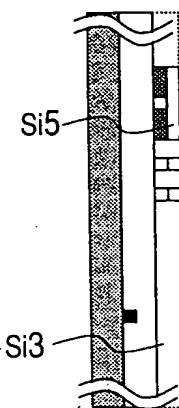


FIG.13E

PATTERN TRANSFER AND ALIGNMENT IN
EXCIMER LASER ANNEALING

ILLUSTRATIVE CONTROL PROCEDURE (1)

SUBSTRATE STAGE OPERATION	ON	
	OFF	
ALIGNMENT, FOCUSING AND OTHER PROCEDURES	ON	
	OFF	
LIGHT IRRADIATION ON SUBSTRATE	ON	
	OFF	

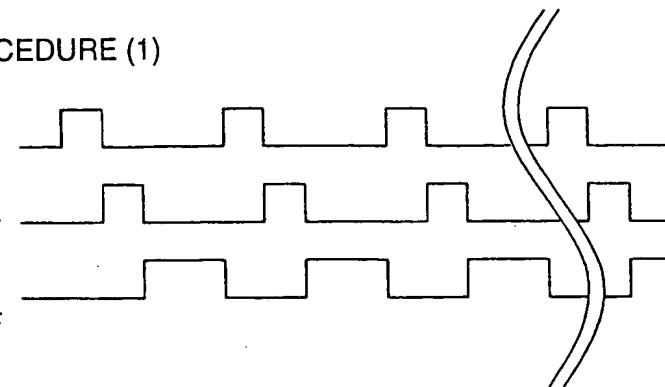
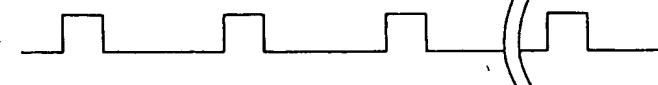
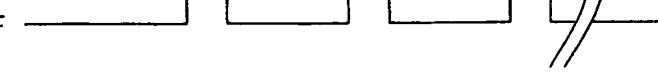


FIG.14A

ILLUSTRATIVE CONTROL PROCEDURE (2)

SUBSTRATE STAGE OPERATION	ON	
	OFF	
ALIGNMENT, FOCUSING AND OTHER PROCEDURES	ON	
	OFF	
MASK STAGE OPERATION	ON	
	OFF	
LIGHT IRRADIATION ON SUBSTRATE	ON	
	OFF	

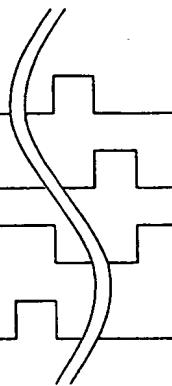
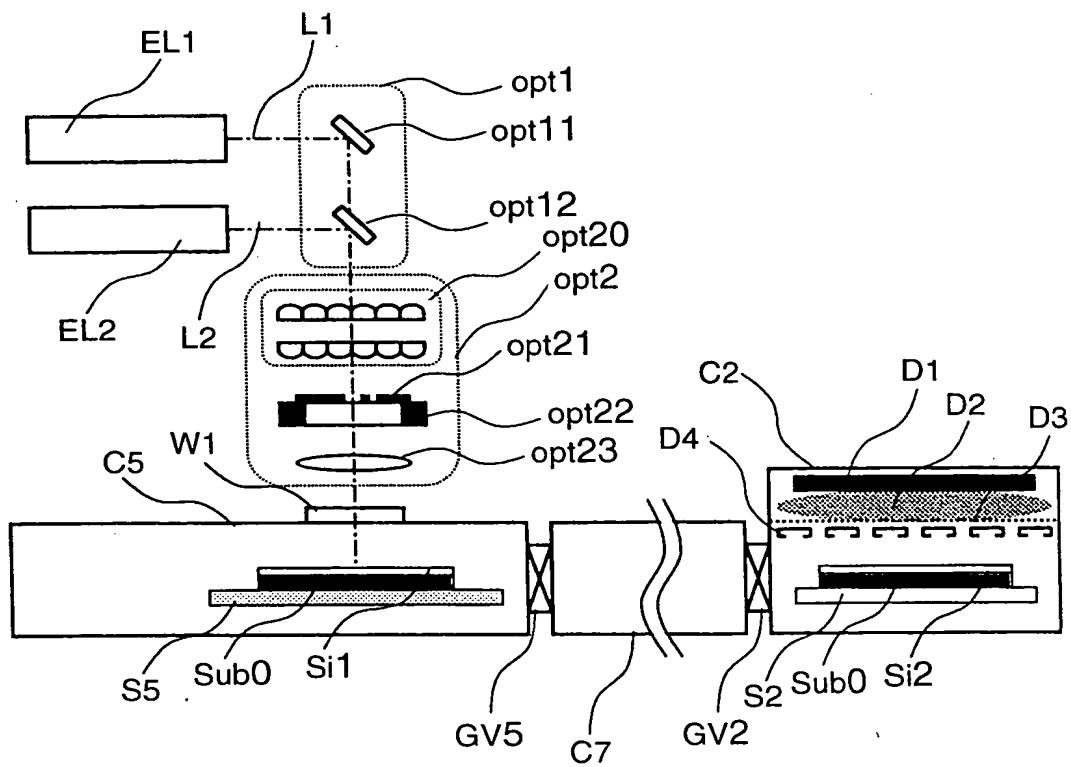


FIG.14B



PLASMA-ENHANCED CVD CHAMBER-SUBSTRATE TRANSFER
CHAMBER-LASER IRRADIATING CHAMBER

FIG.15

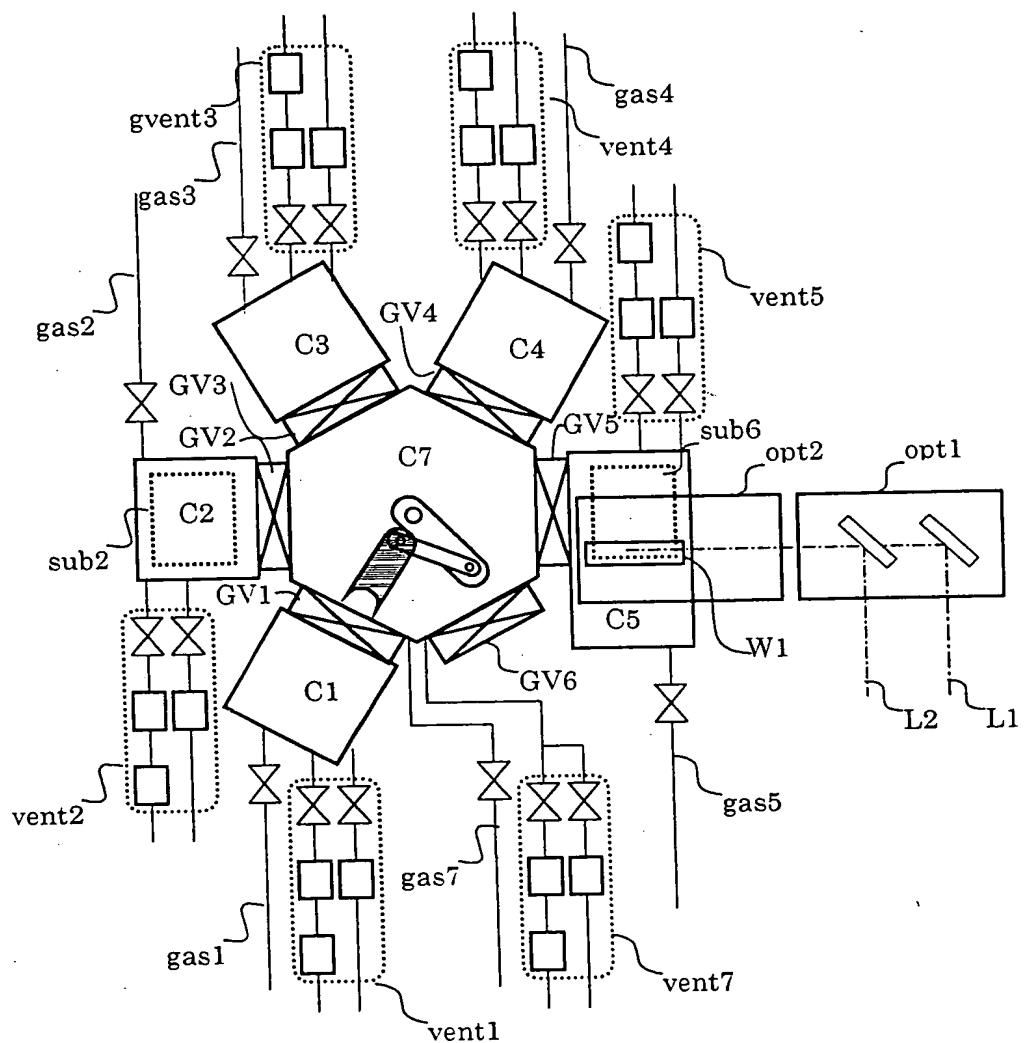


FIG. 16

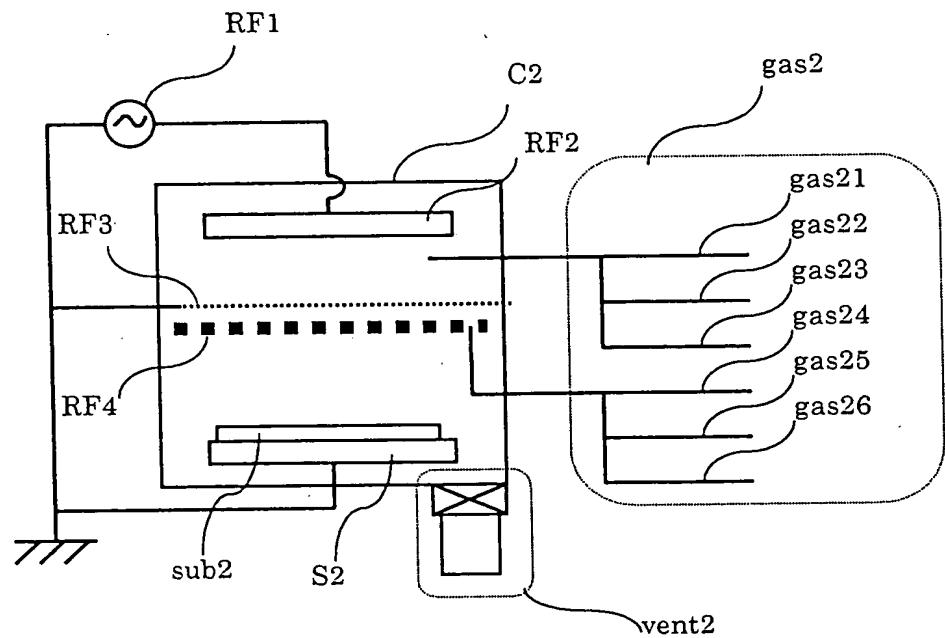


FIG. 17

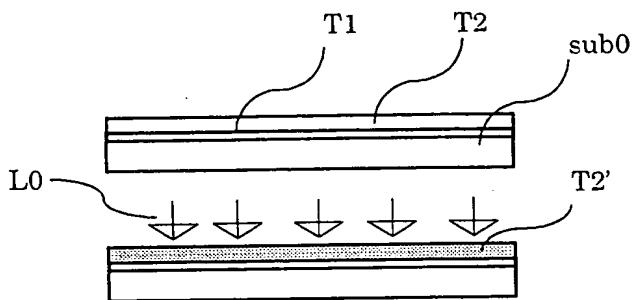


FIG. 18A

FIG. 18B

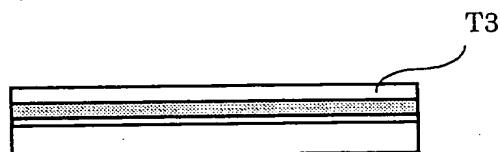


FIG. 18C

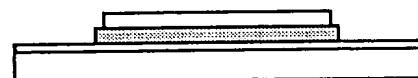


FIG. 18D

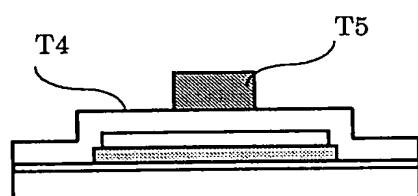


FIG. 18E

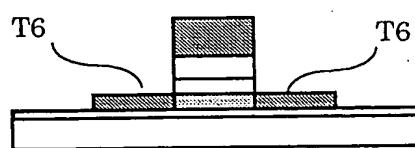


FIG. 18F1

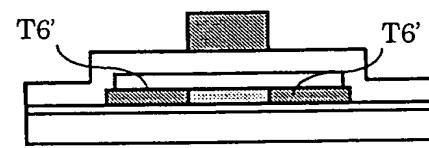


FIG. 18F2

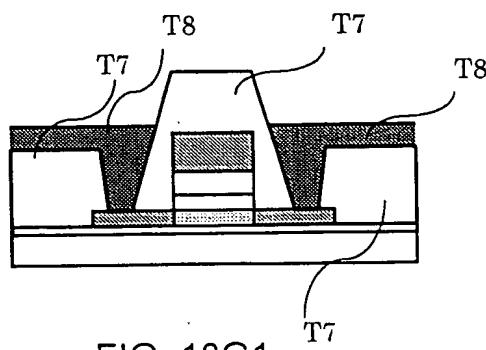


FIG. 18G1

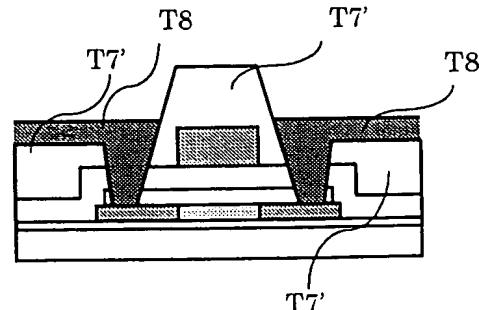


FIG. 18G2

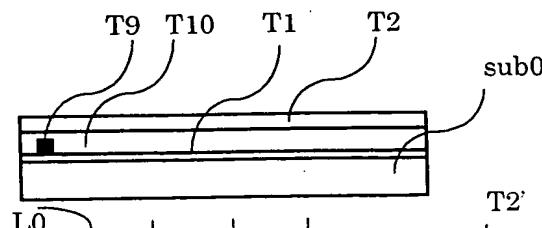


FIG. 19A

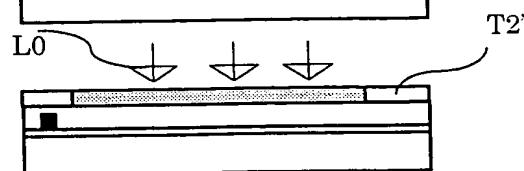


FIG. 19B

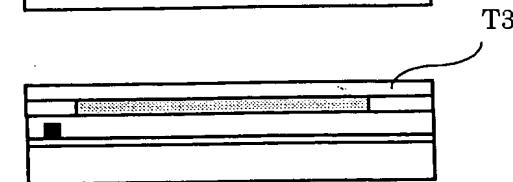


FIG. 19C

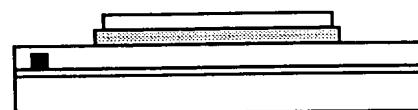


FIG. 19D

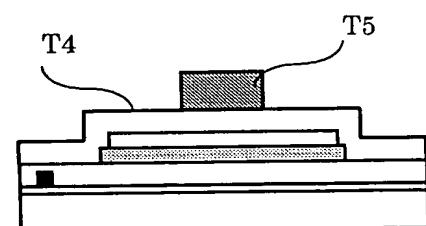


FIG. 19E

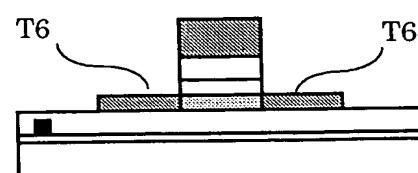


FIG. 19F1

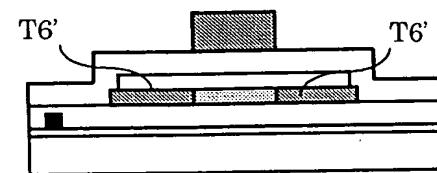


FIG. 19F2

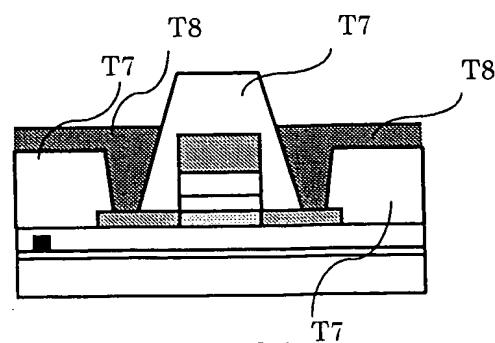


FIG. 19G1

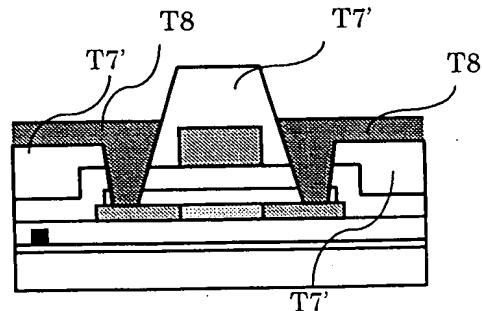


FIG. 19G2

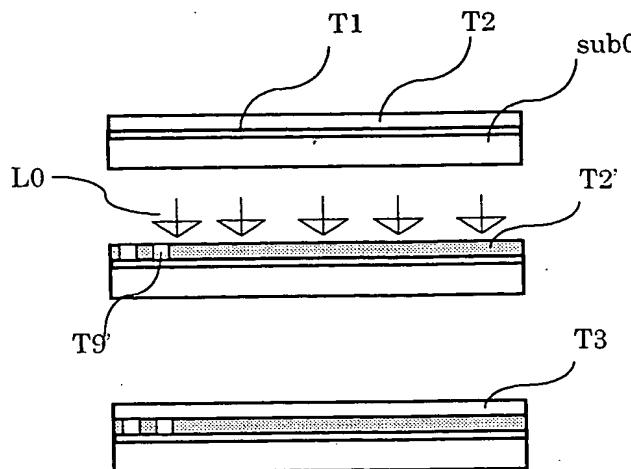


FIG. 20A

FIG. 20B

FIG. 20C



FIG. 20D

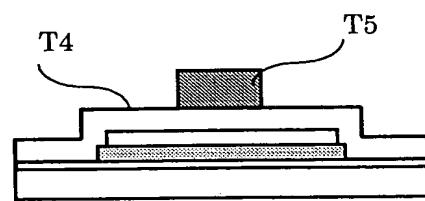


FIG. 20E

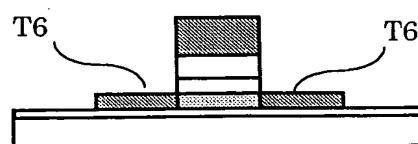


FIG. 20G1

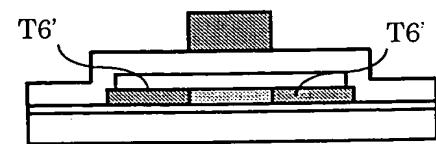


FIG. 20G2

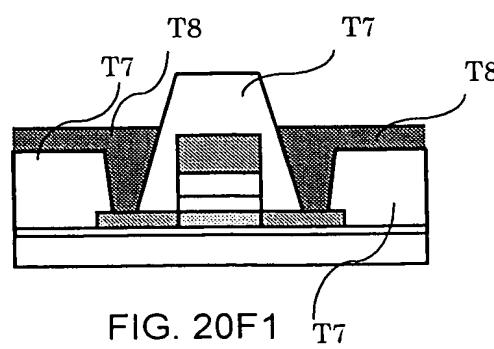


FIG. 20F1

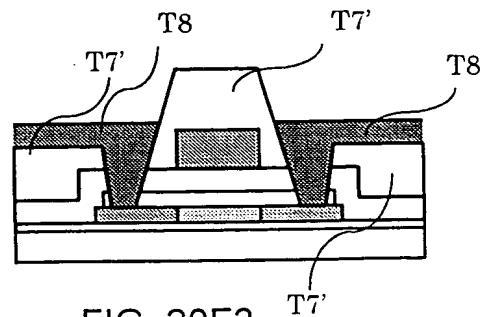


FIG. 20F2

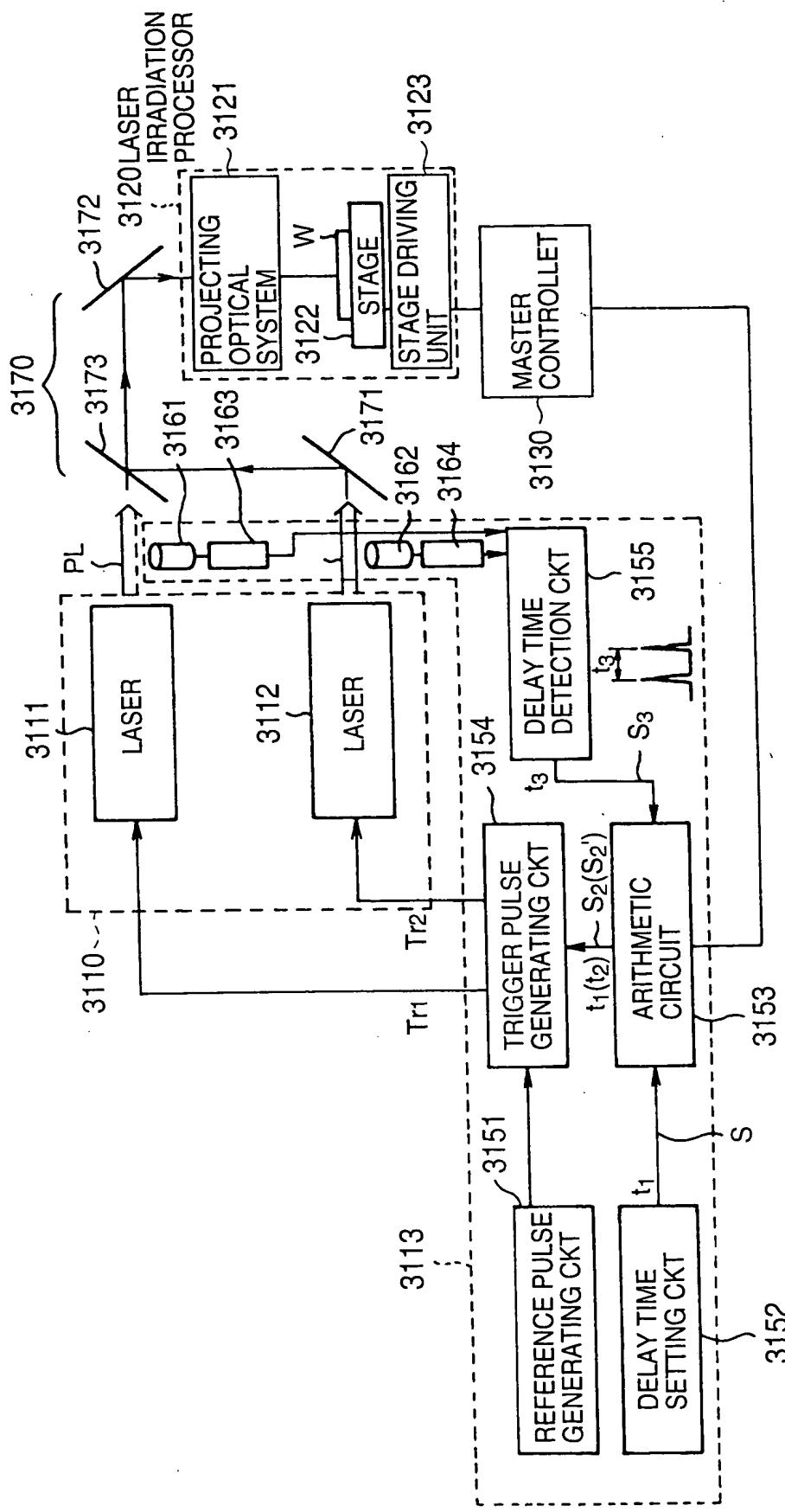


FIG. 21

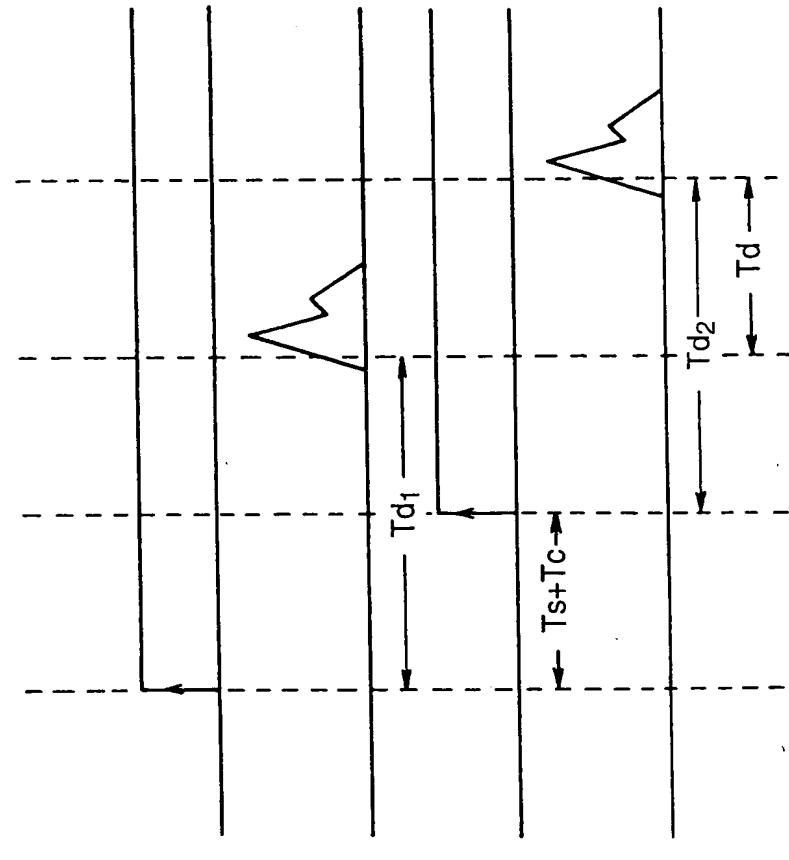


FIG.22A FIRST LASING TRIGGER

FIG.22B FIRST LASING PULSE

FIG.22C TRIGGER DELAY CIRCUIT
OUTPUT/SECOND
LASING TRIGGER

FIG.22D SECOND LASING PULSE

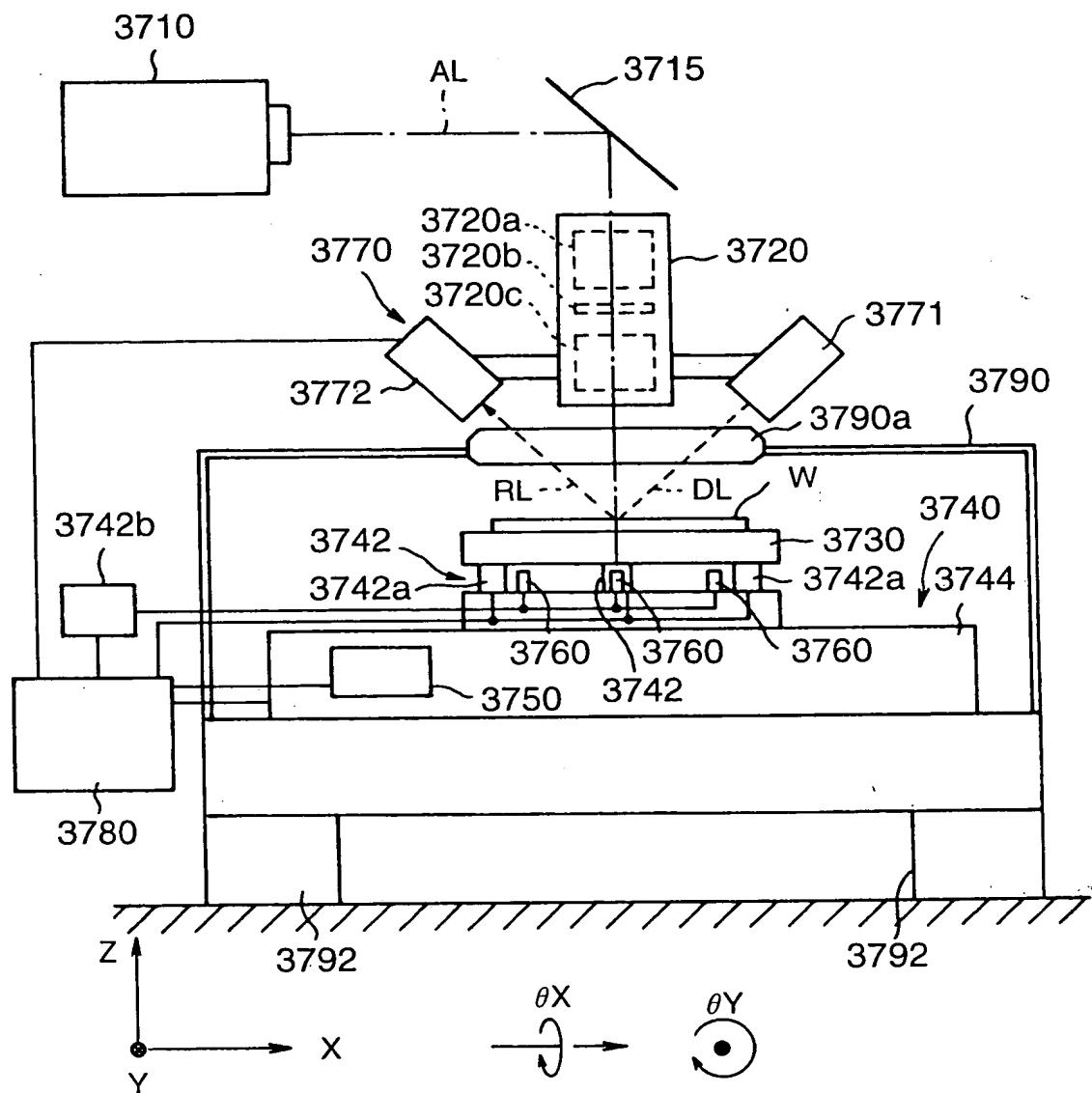


FIG.23

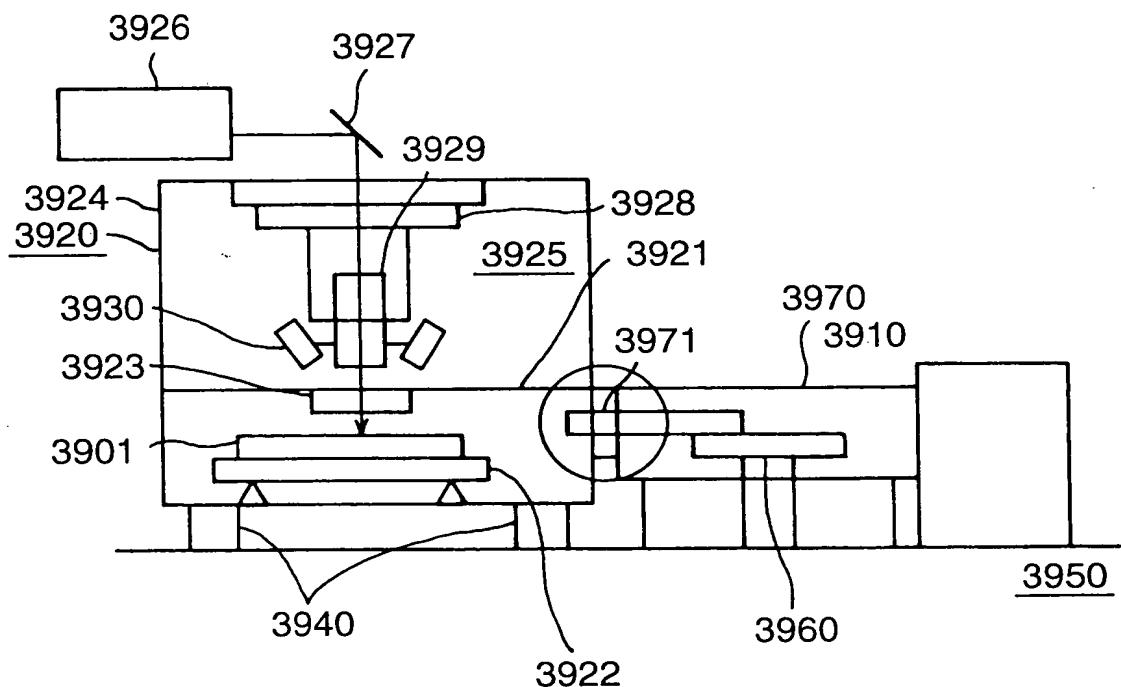


FIG.24

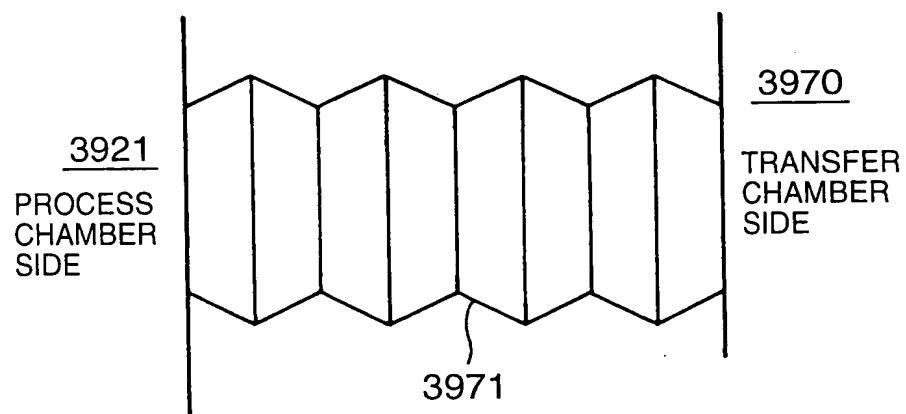


FIG.25

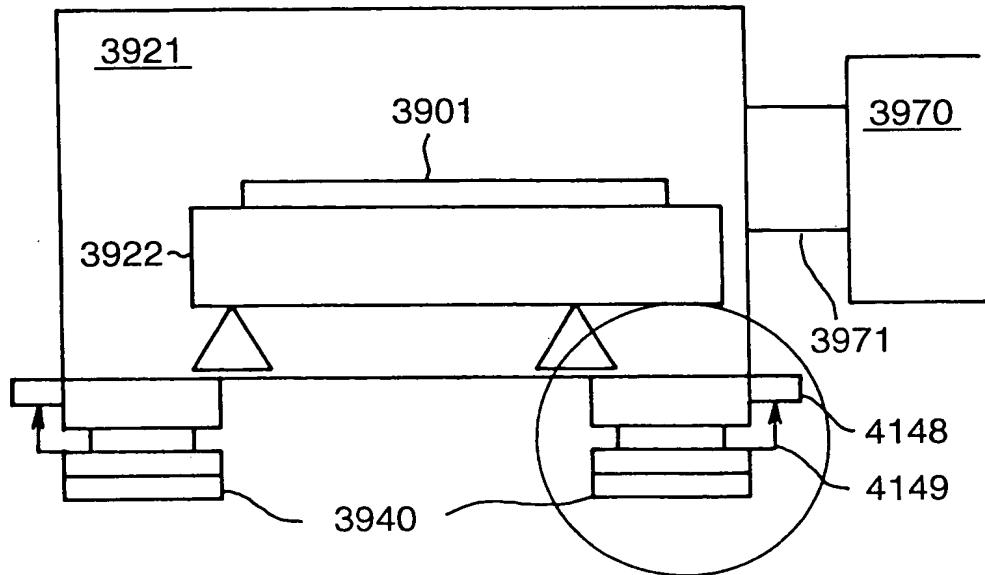


FIG.26

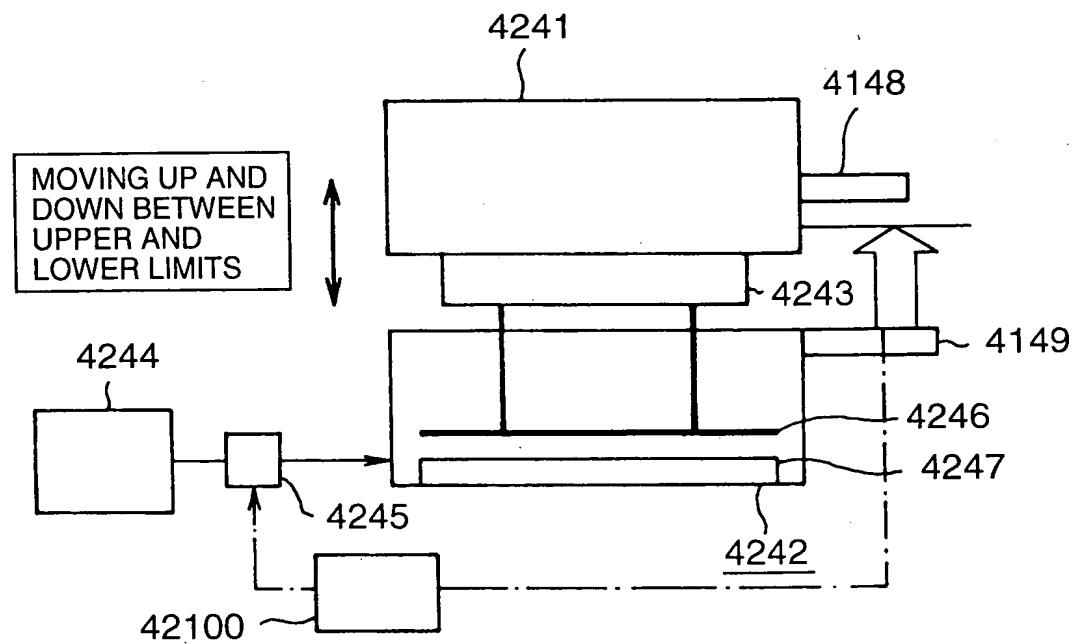


FIG.27

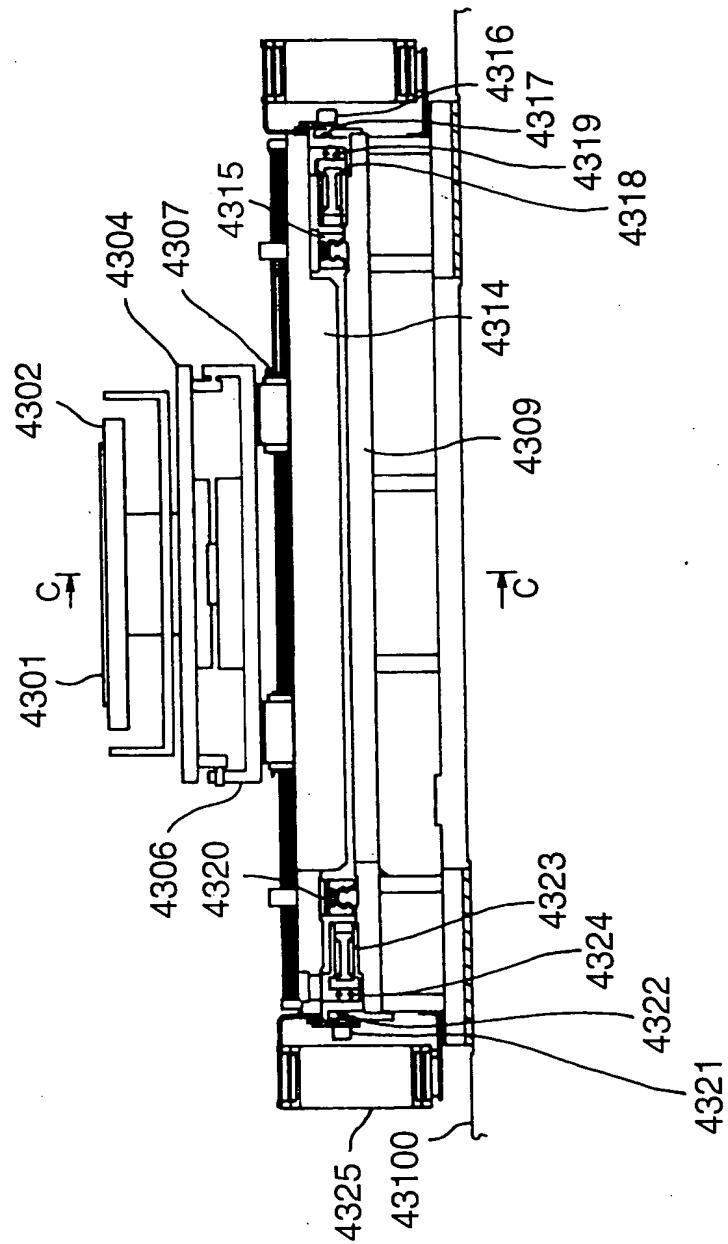
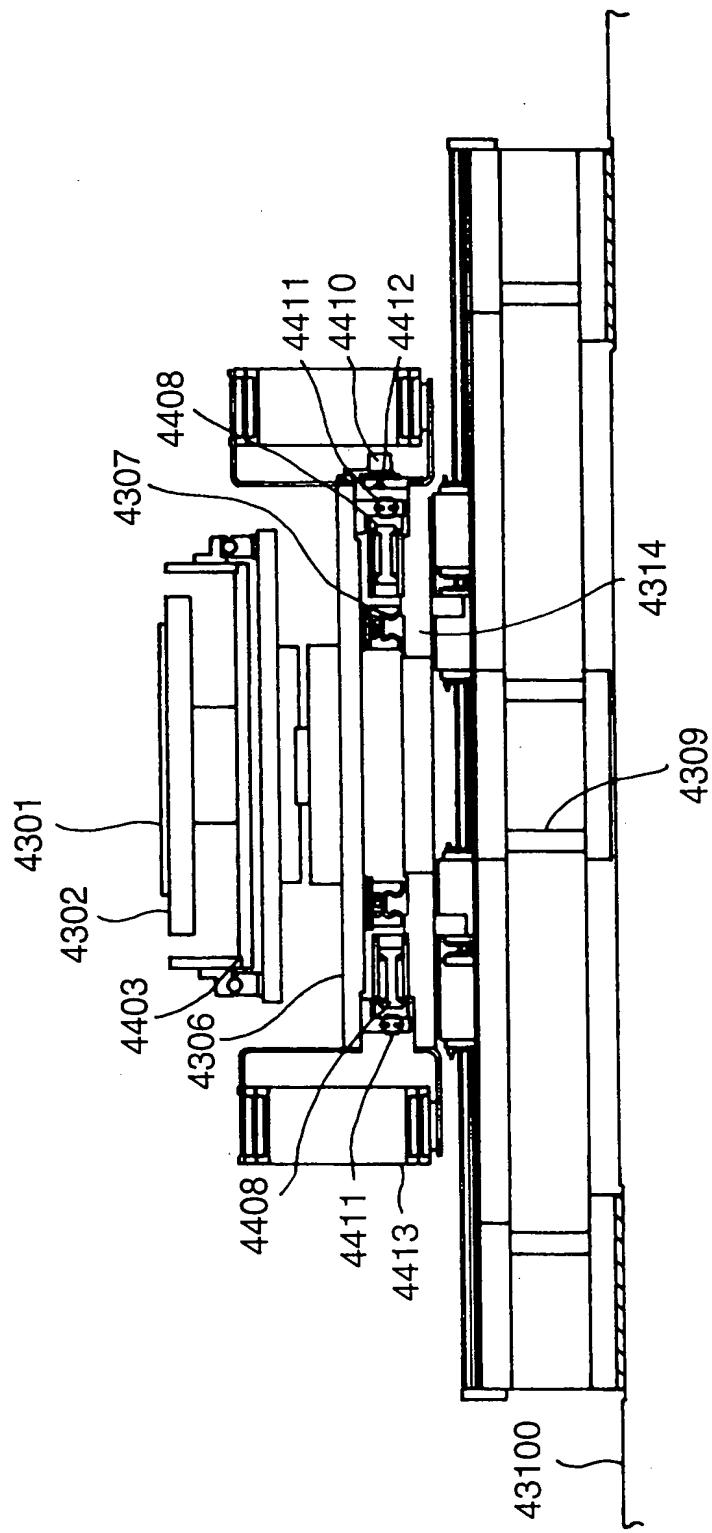


FIG.28



C-C

FIG.29

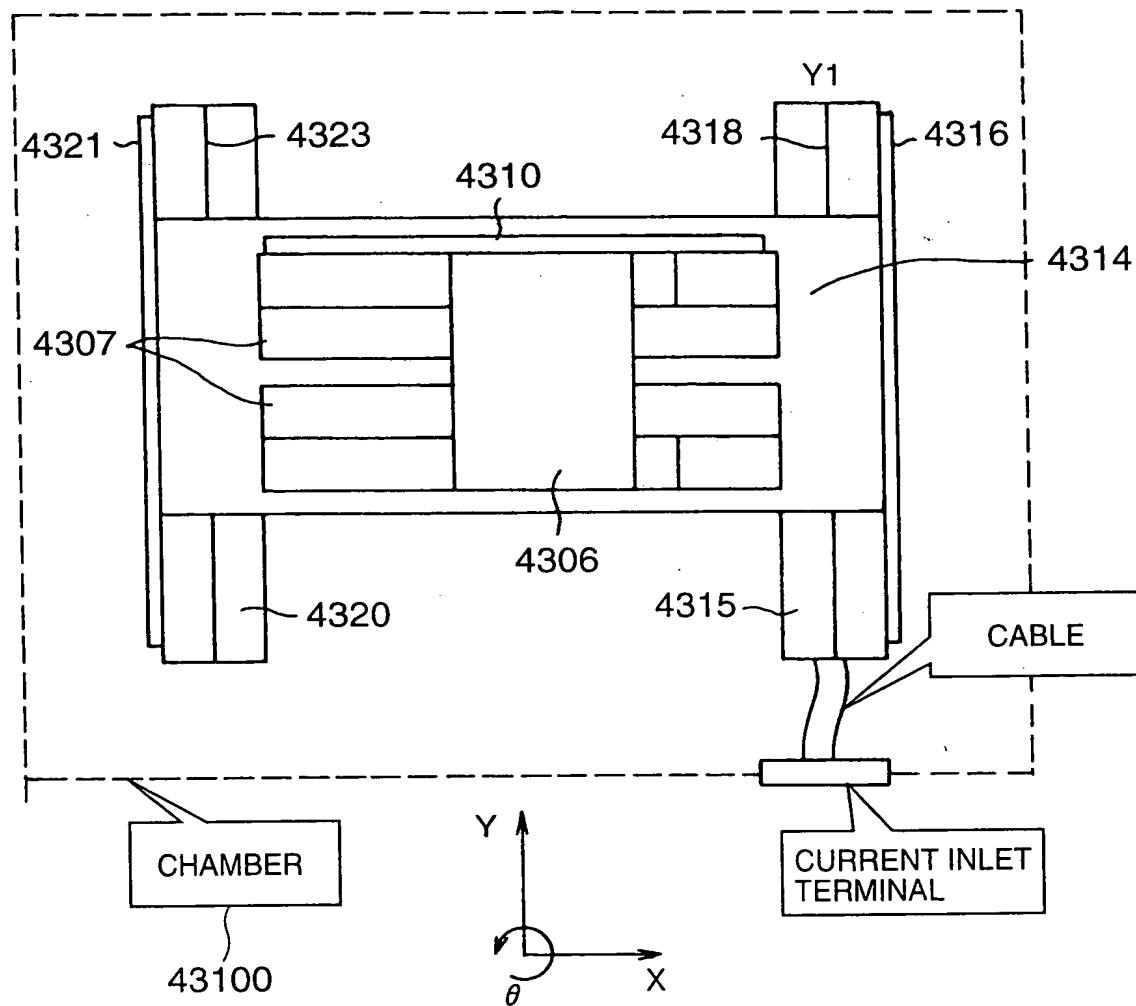


FIG.30

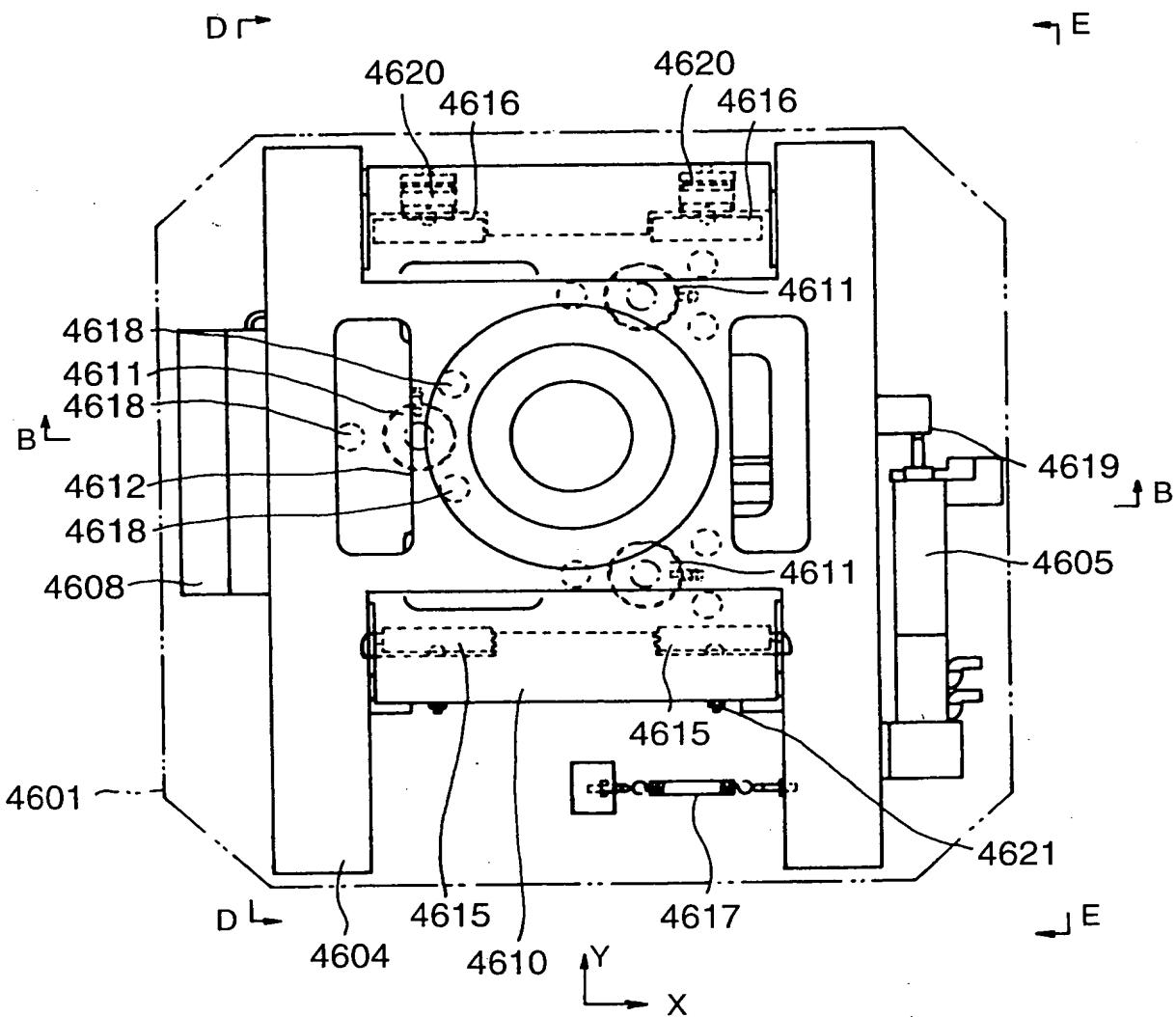


FIG.31

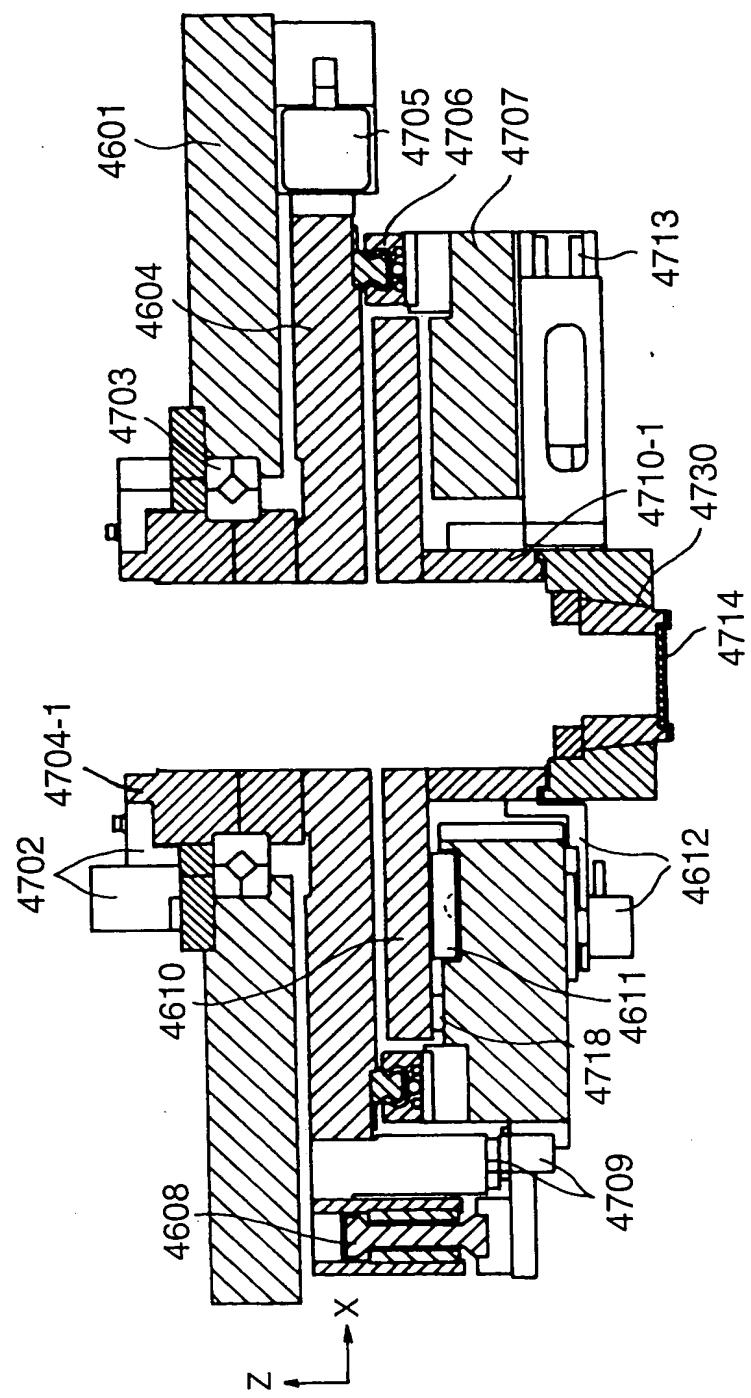


FIG.32

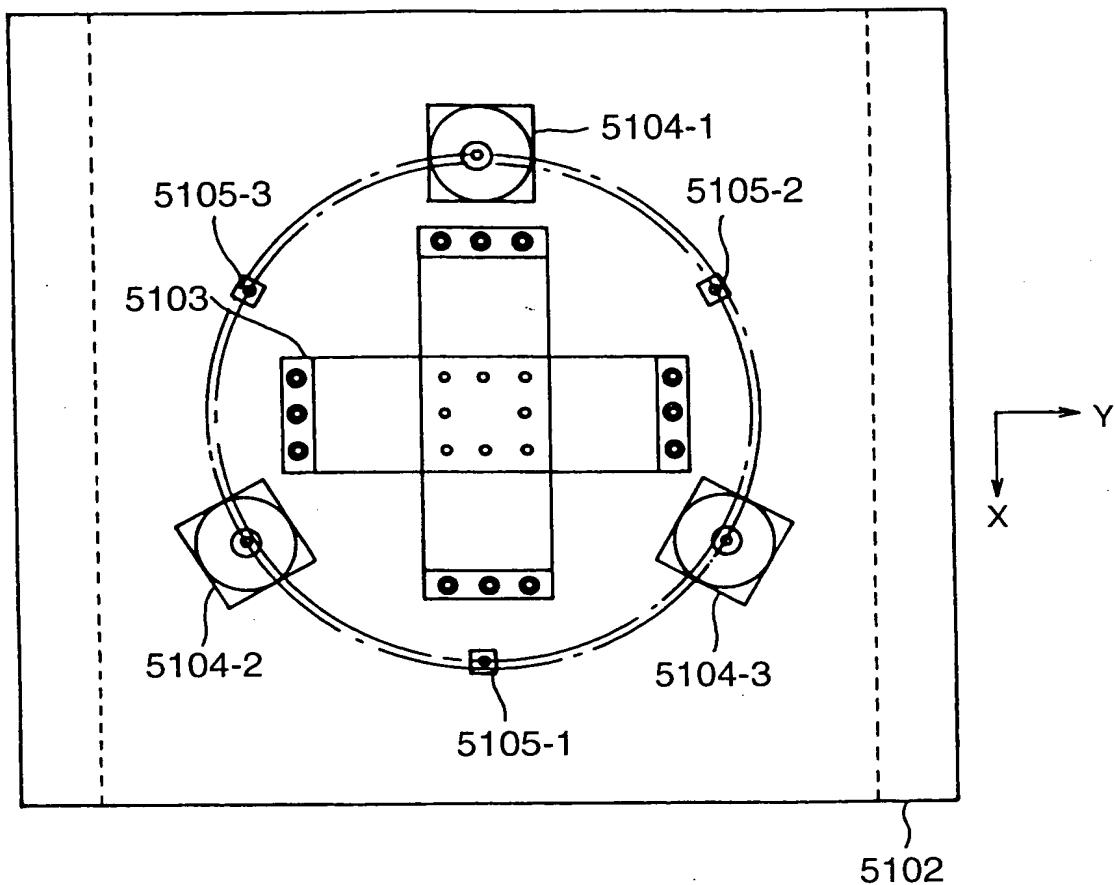


FIG.33

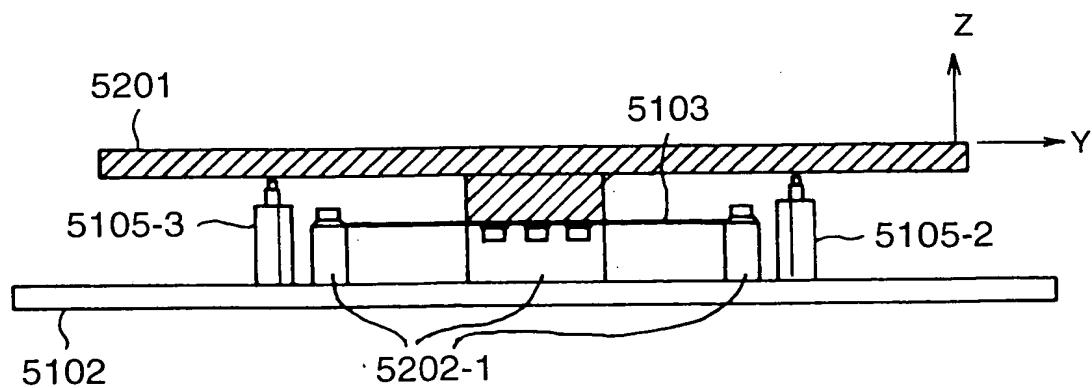


FIG.34

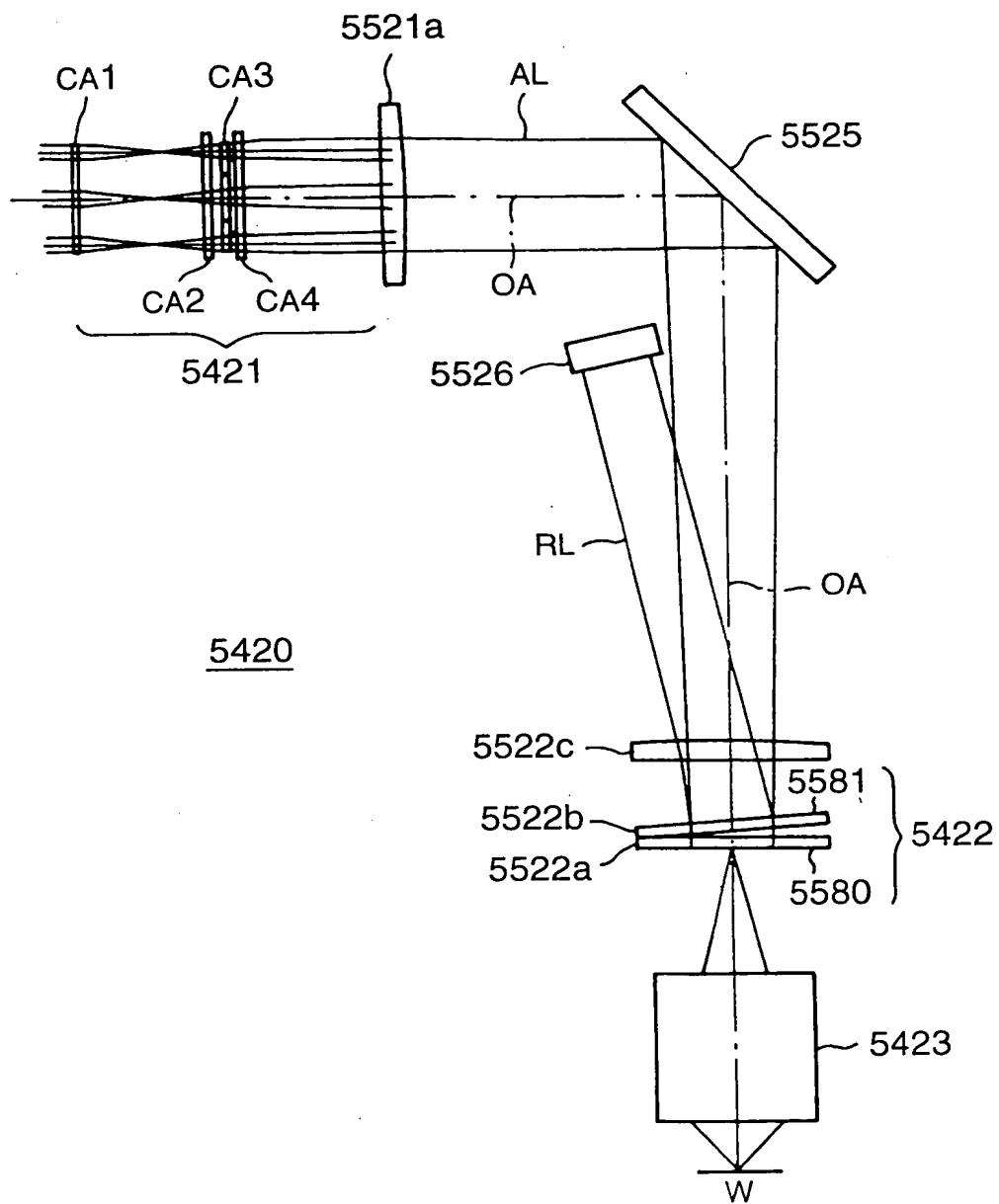


FIG.35

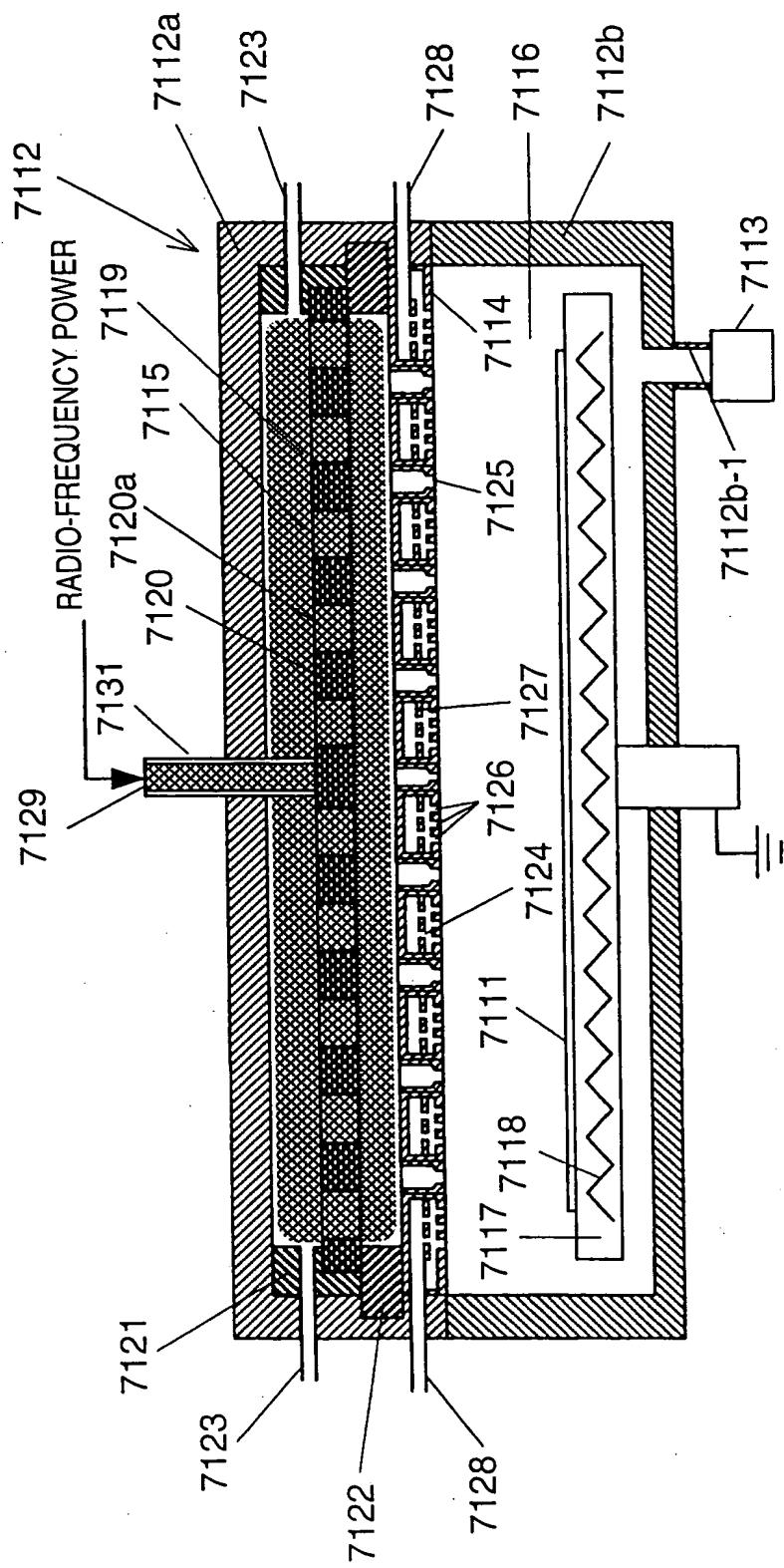


FIG. 36

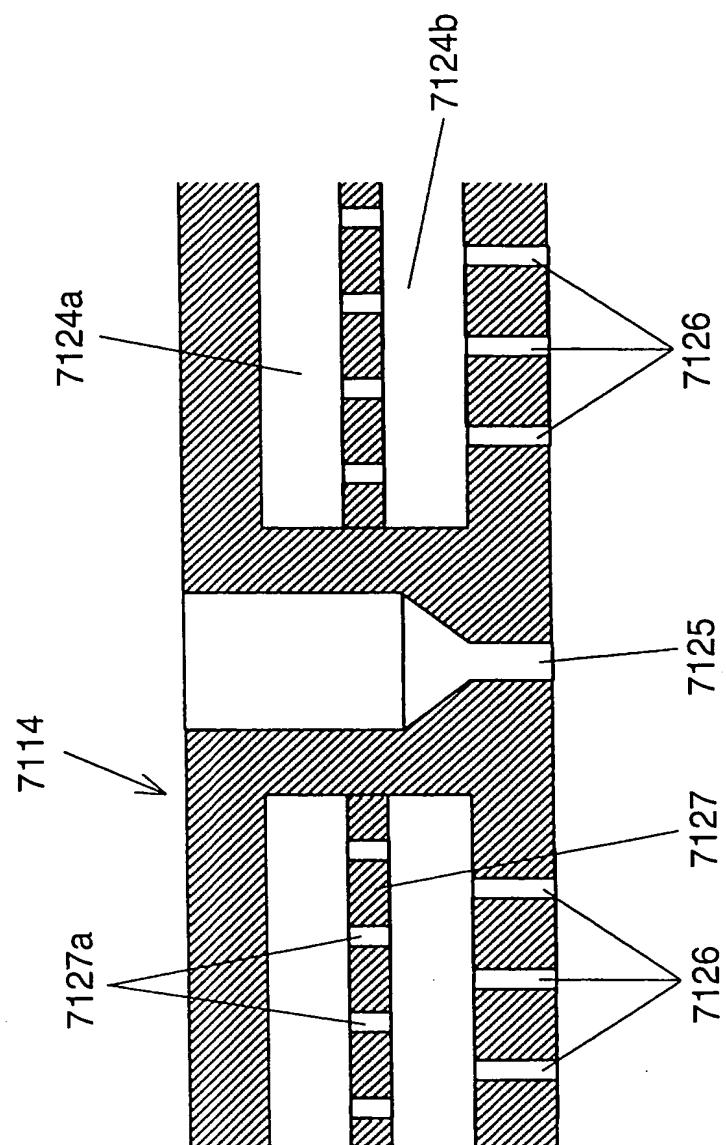


FIG.37

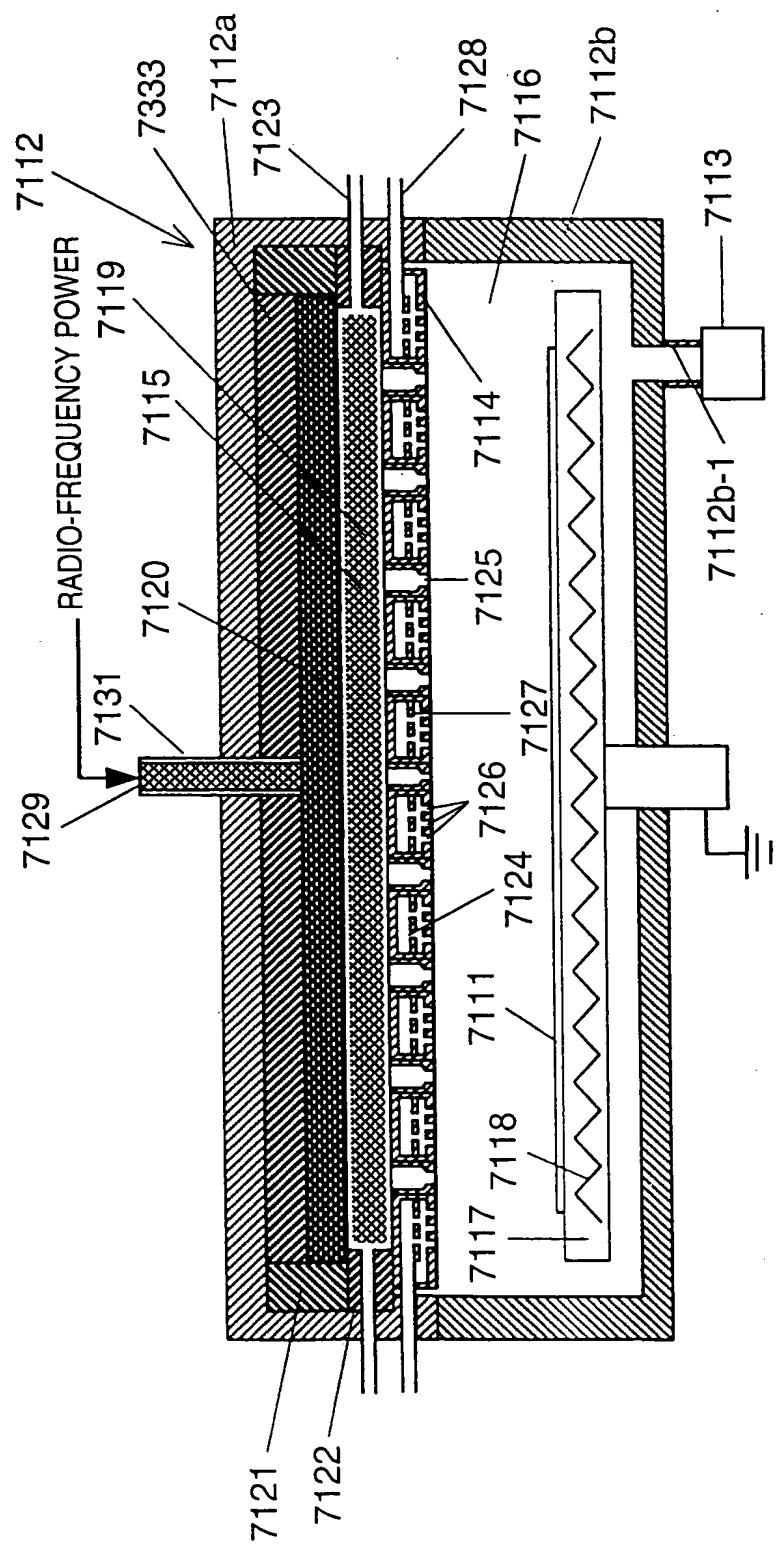


FIG. 38

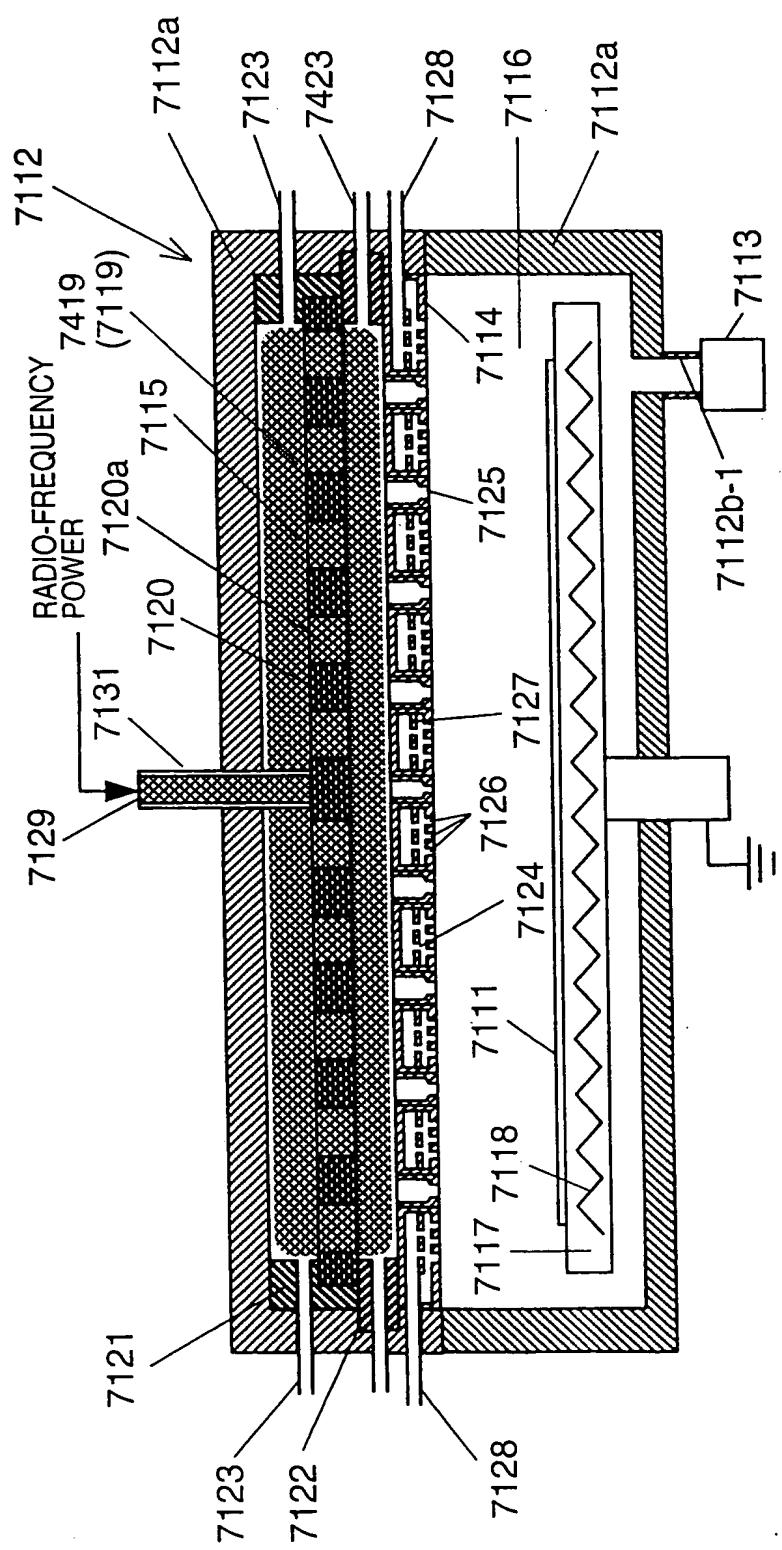


FIG.39

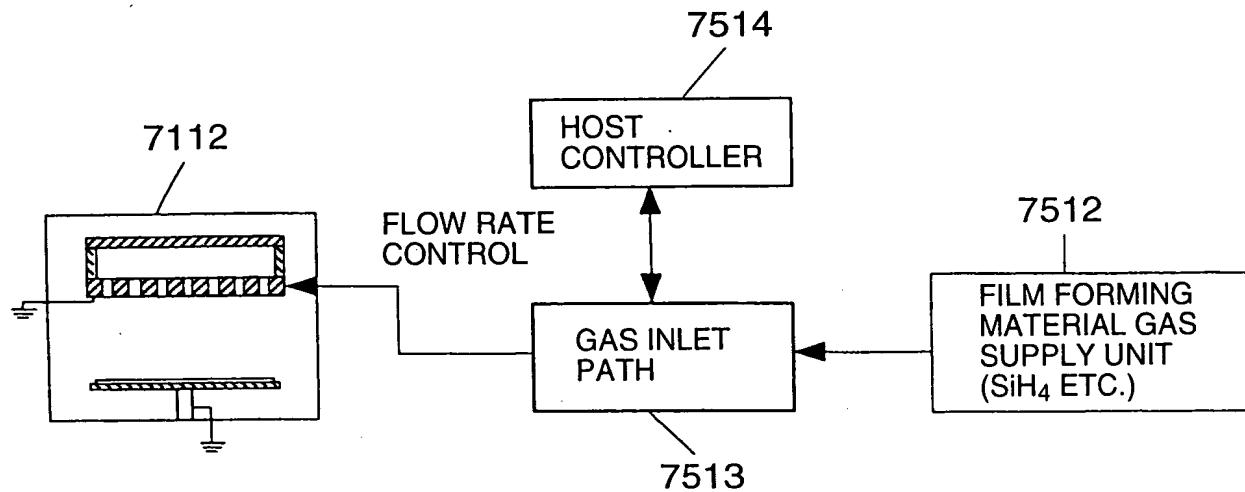


FIG.40

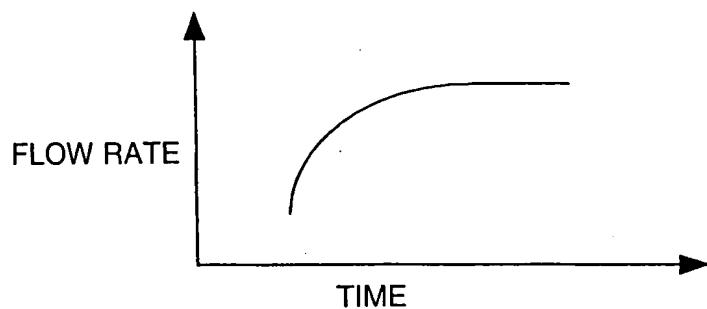
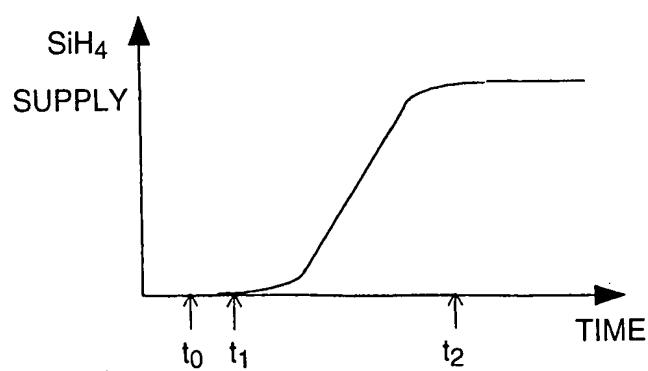


FIG.41



t_0 : START OF O₂ DISCHARGE
 t_1 : START OF SiH₄ SUPPLY
 t_2 : SiH₄ SUPPLY ATTAINS A CONSTANT LEVEL

FIG.42

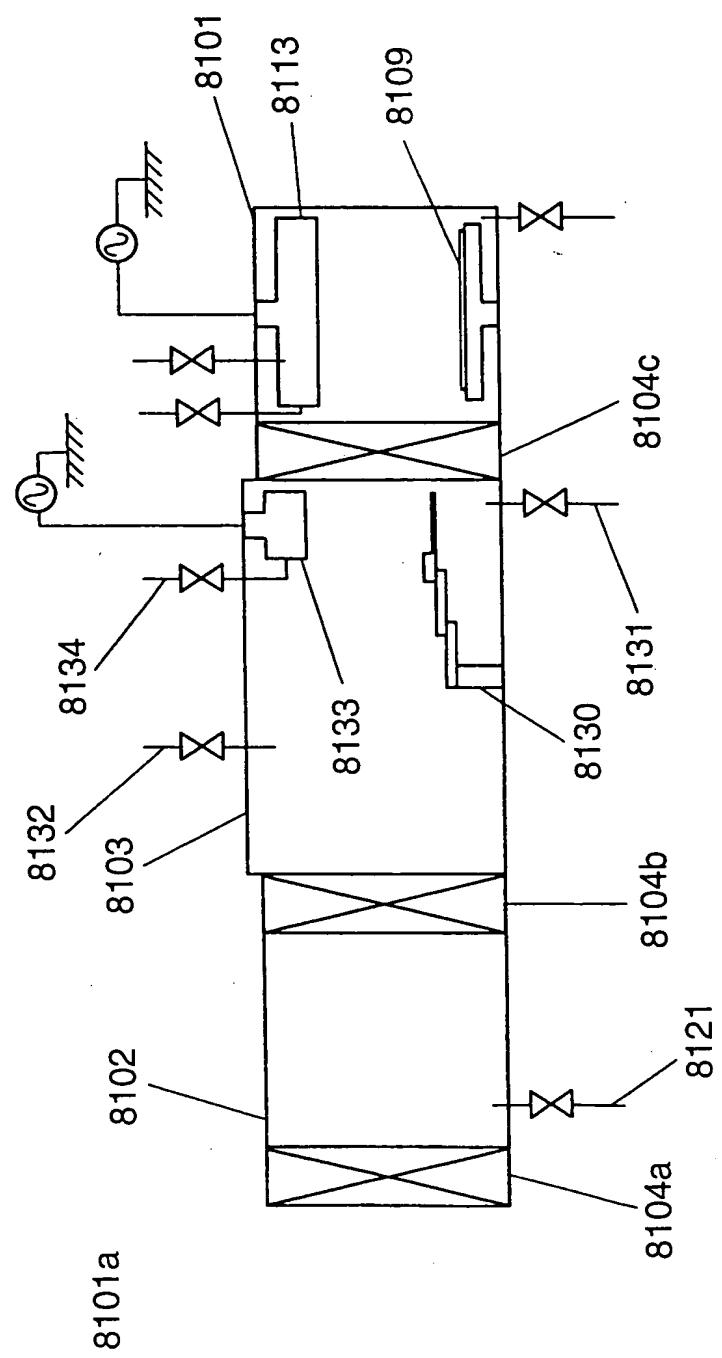
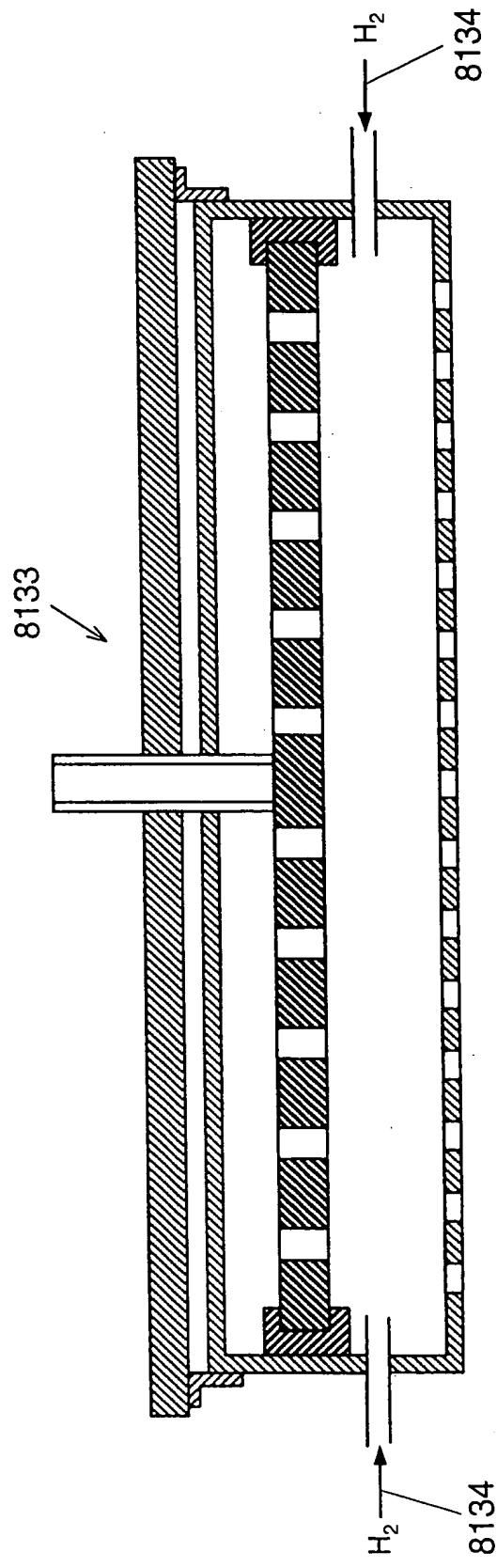


FIG.43

FIG.44



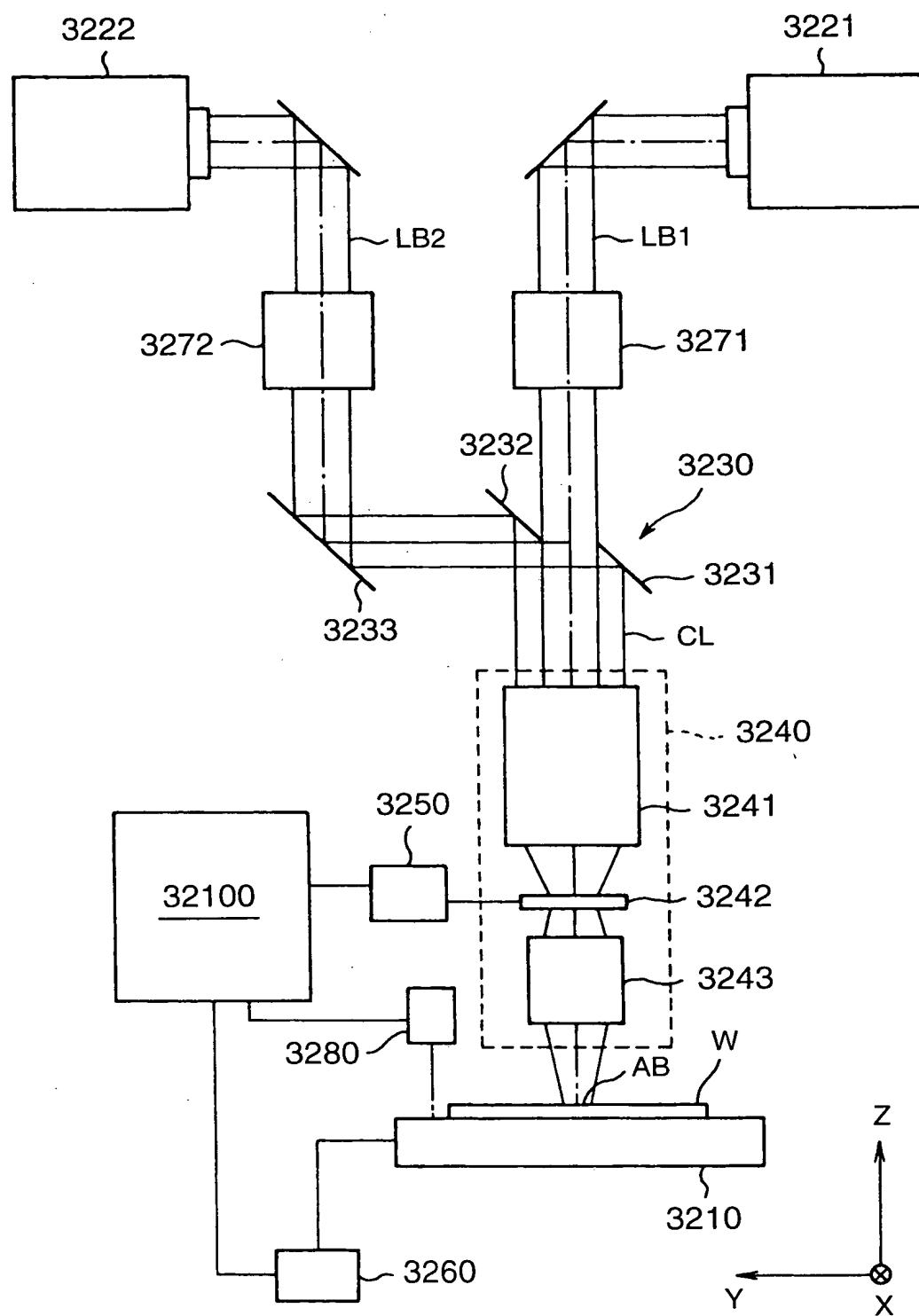


FIG.45

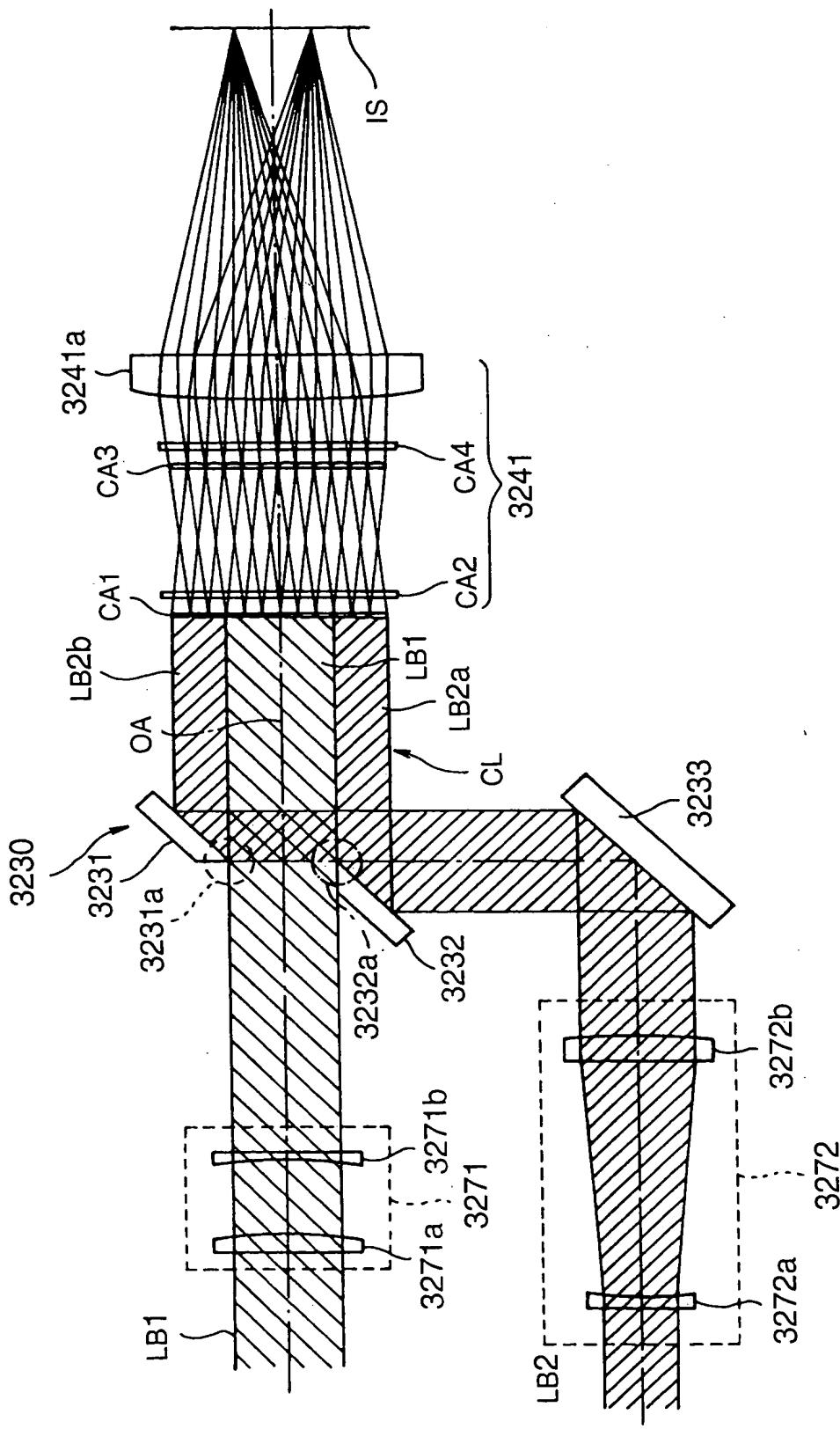


FIG. 46

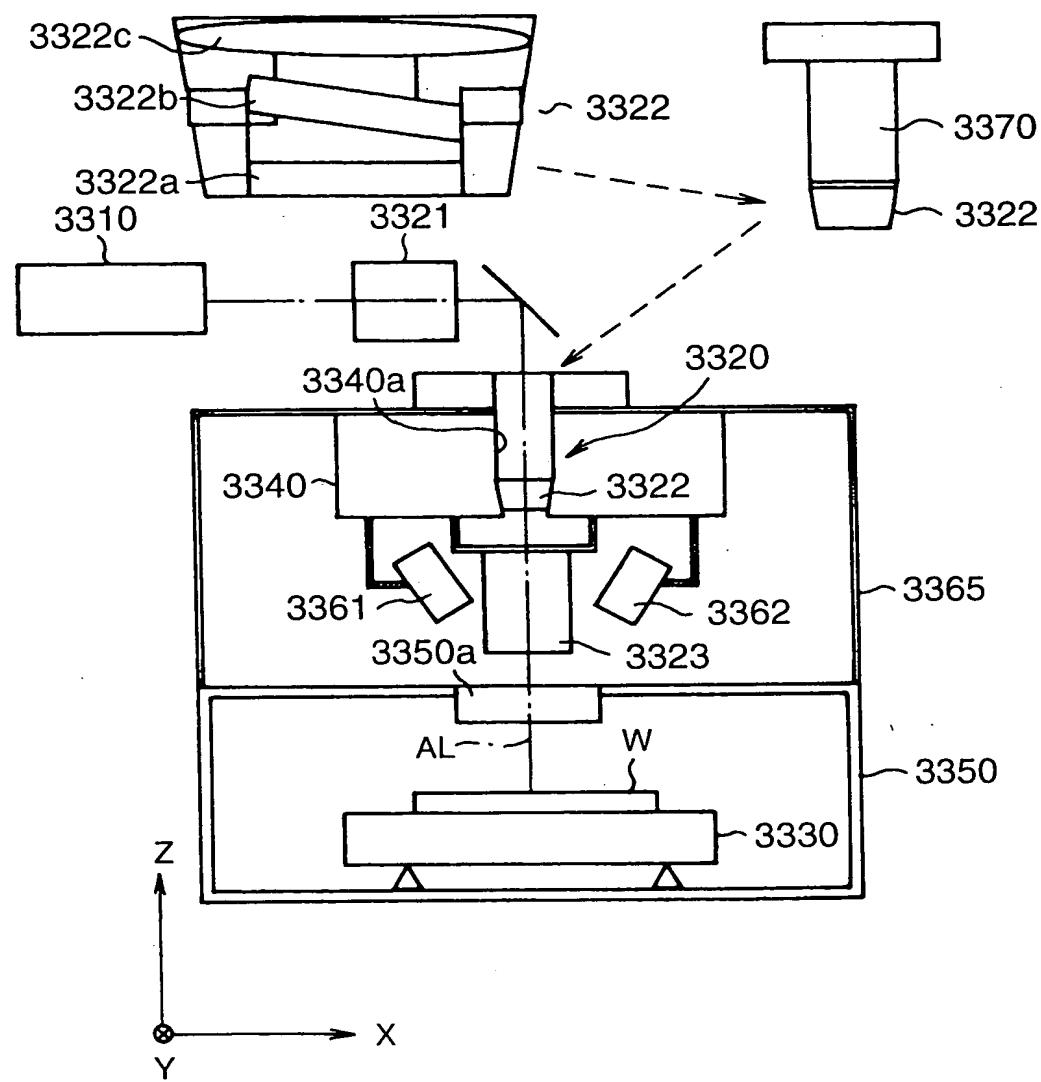


FIG.47

FIG.48A

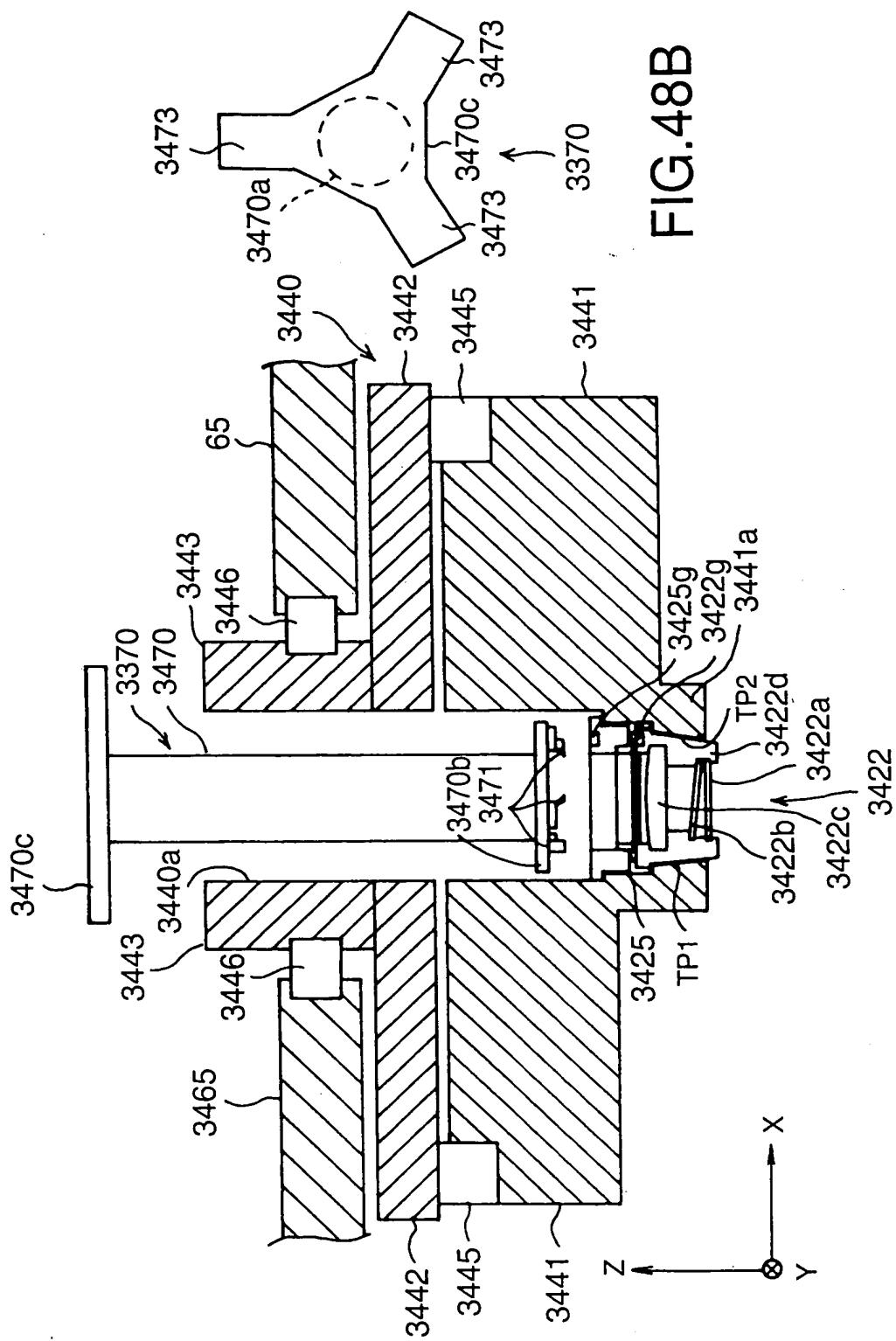
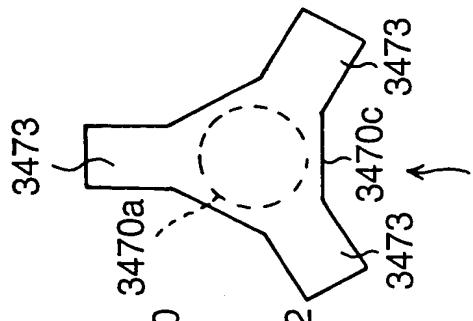


FIG.48B



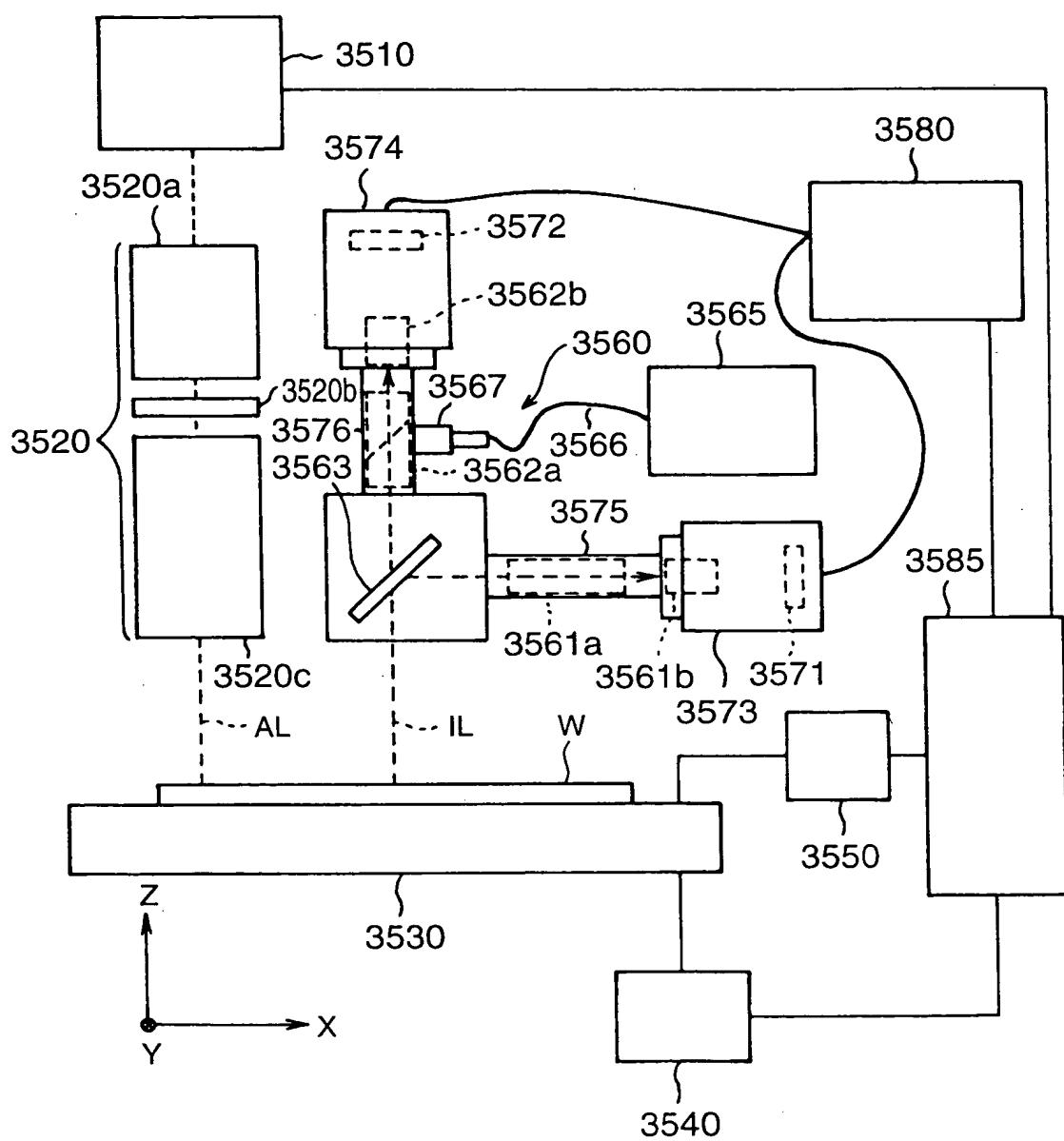


FIG.49

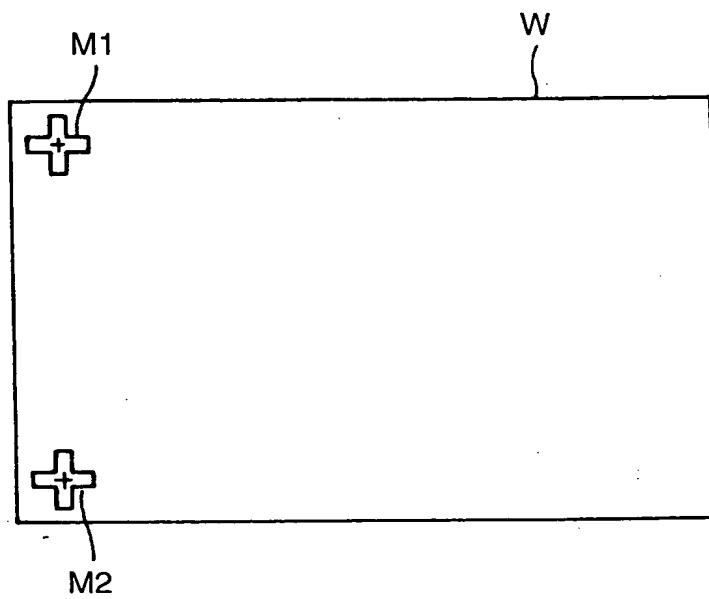


FIG.50

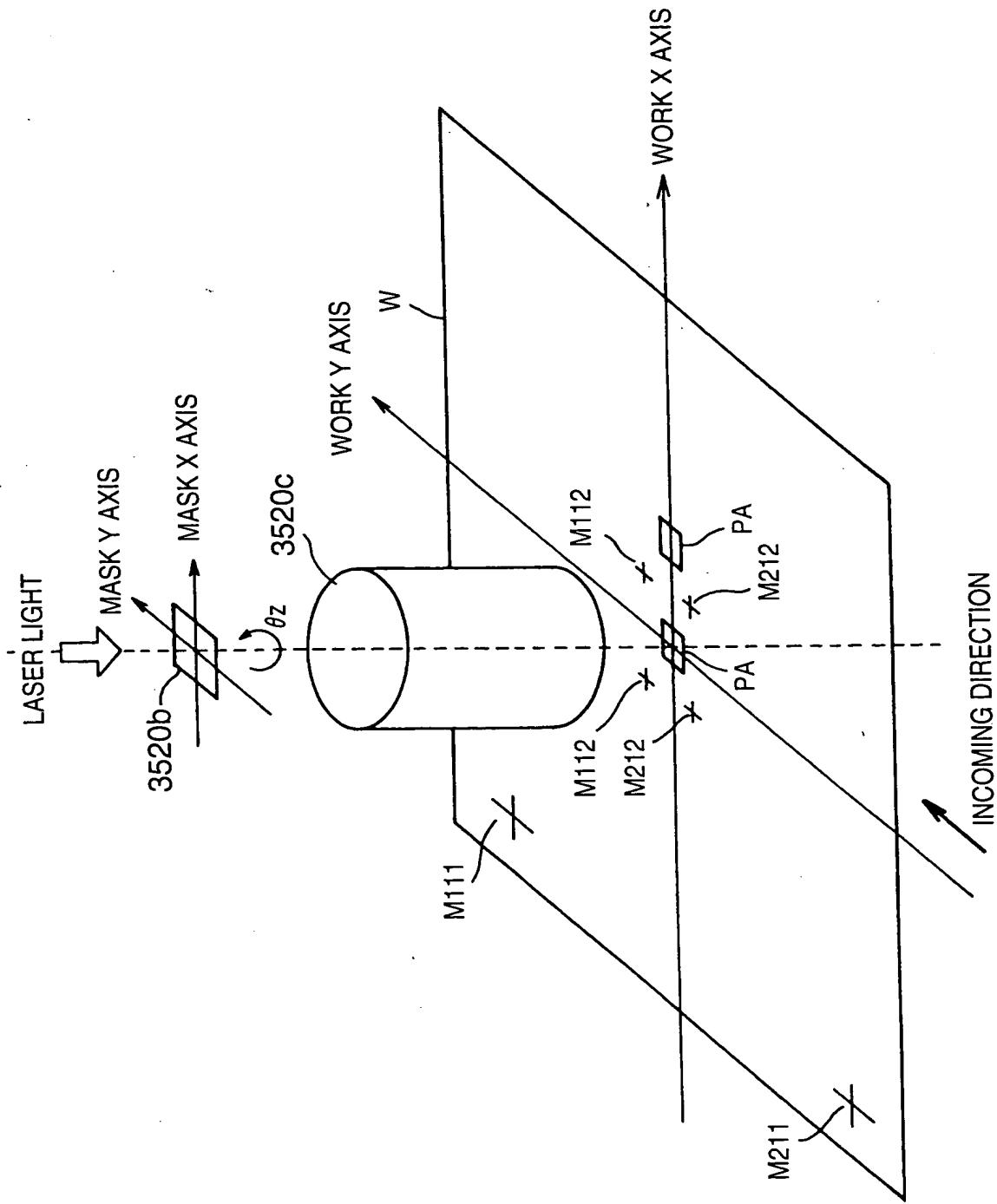


FIG. 51

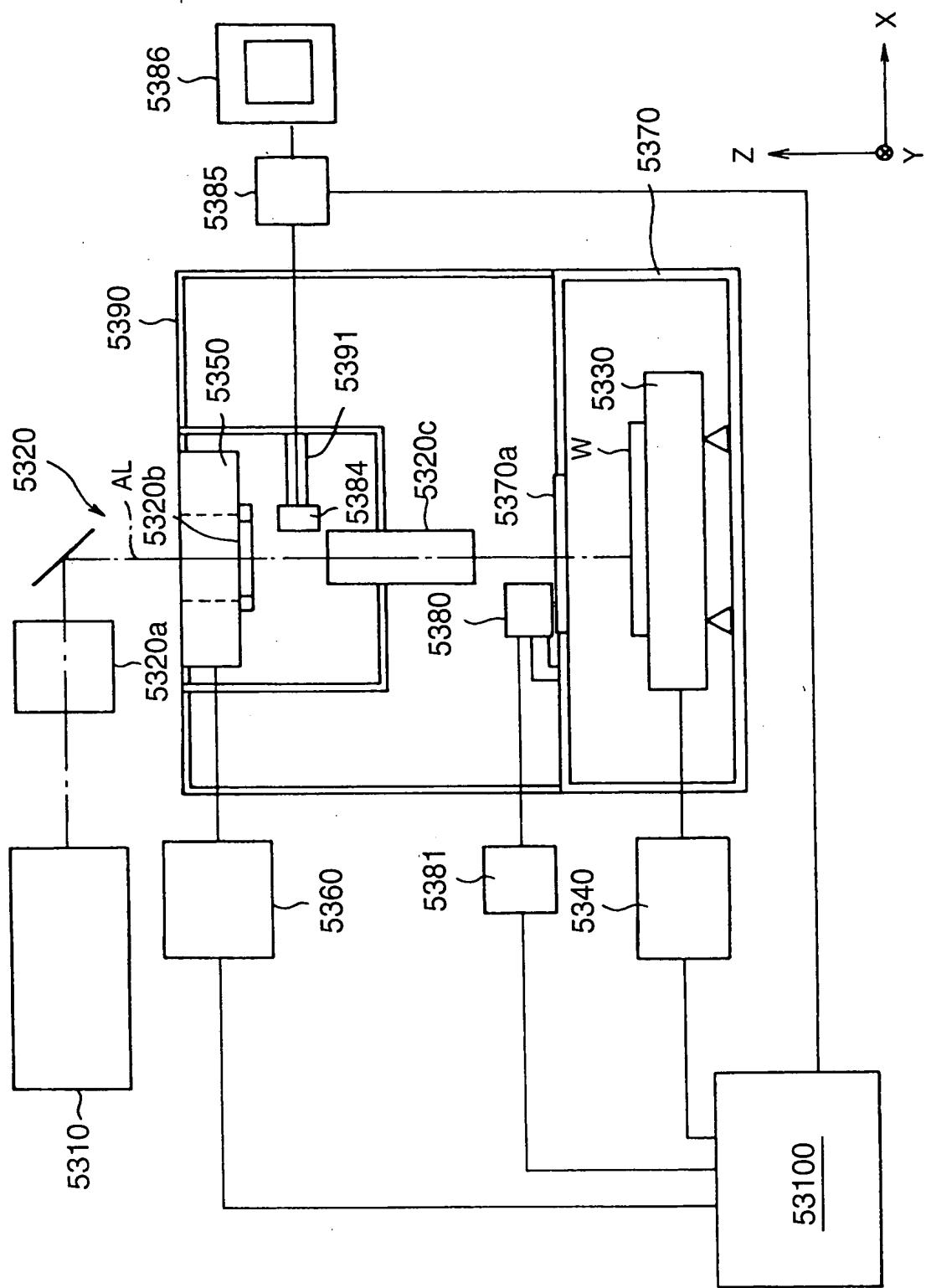


FIG. 52